



Upgrade of the ALICE Inner Tracking System

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EMMI, GSI, Darmstadt
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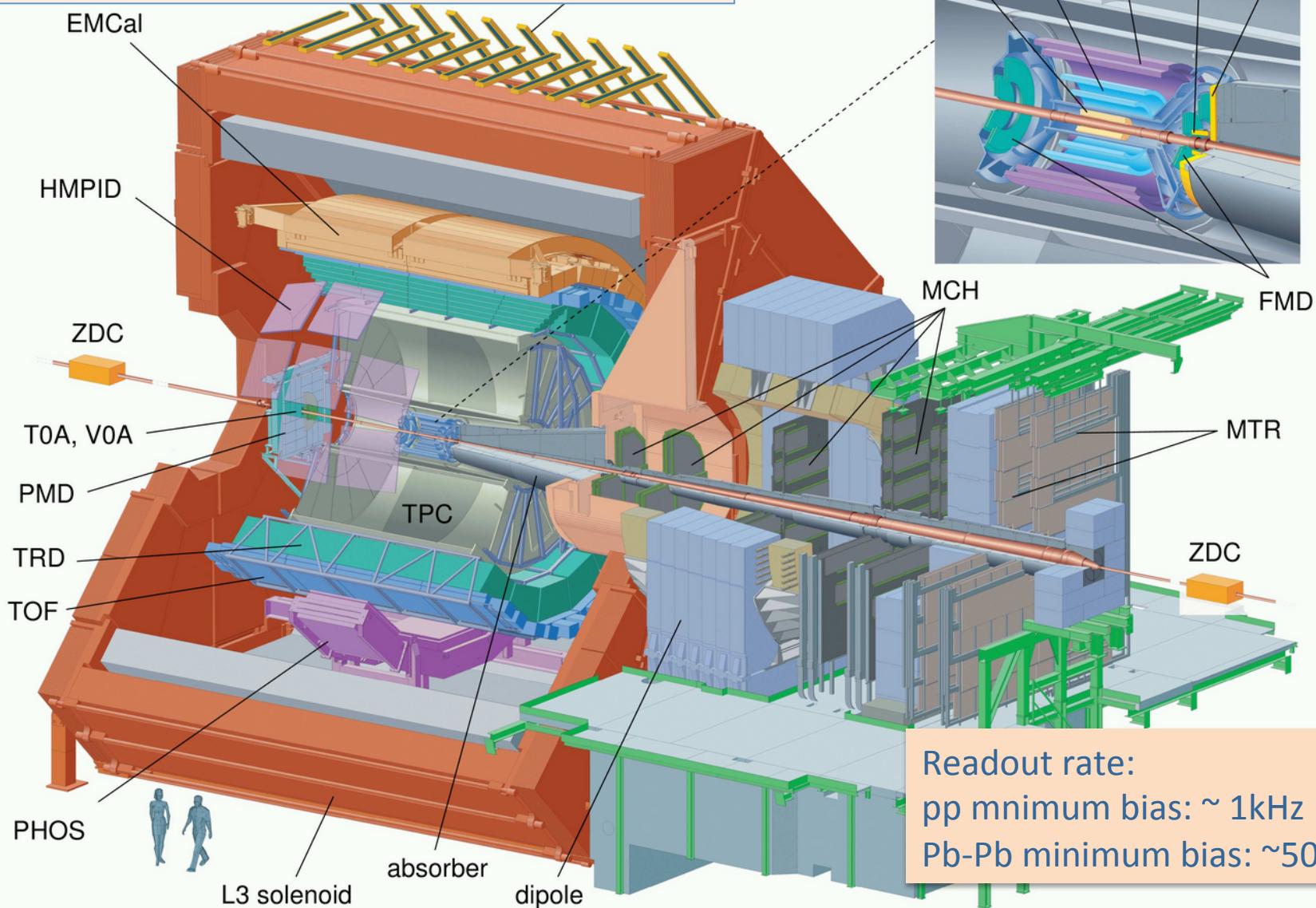
Upgrade of the ALICE Inner Tracking System

OUTLINE

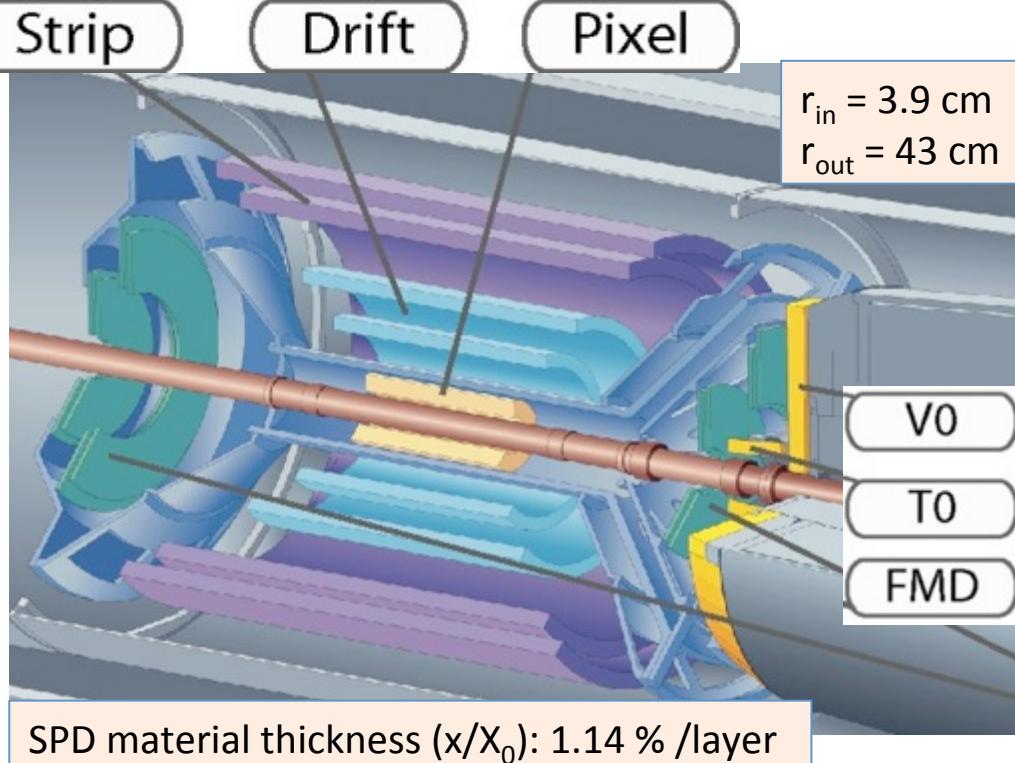
- ALICE current set-up and Inner Tracking System
- ALICE upgrade motivations and strategy
- ITS upgrade design objectives
- ITS upgrade layout and main components
- Detector simulated performance: some examples

The Current ALICE Detector

Only LHC experiment dedicated to HI collisions



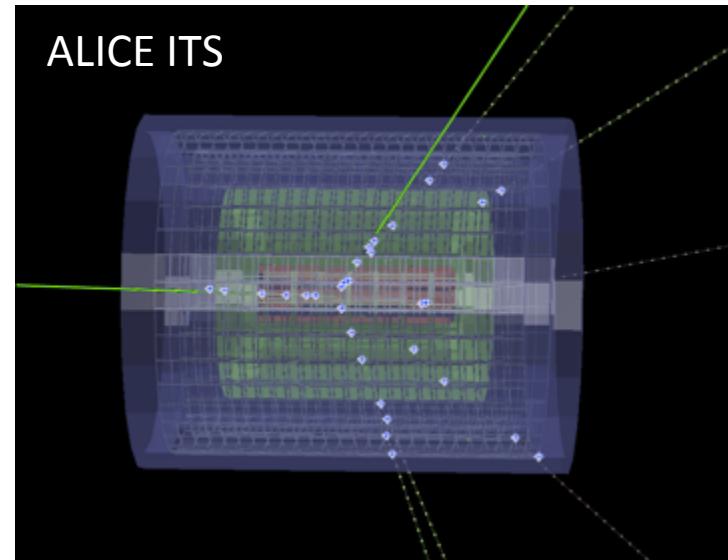
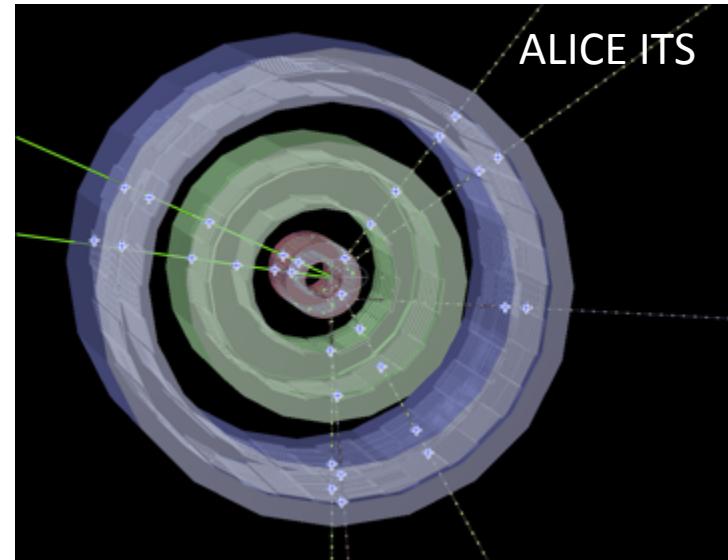
The Current ALICE Inner Tracking System



Current ITS

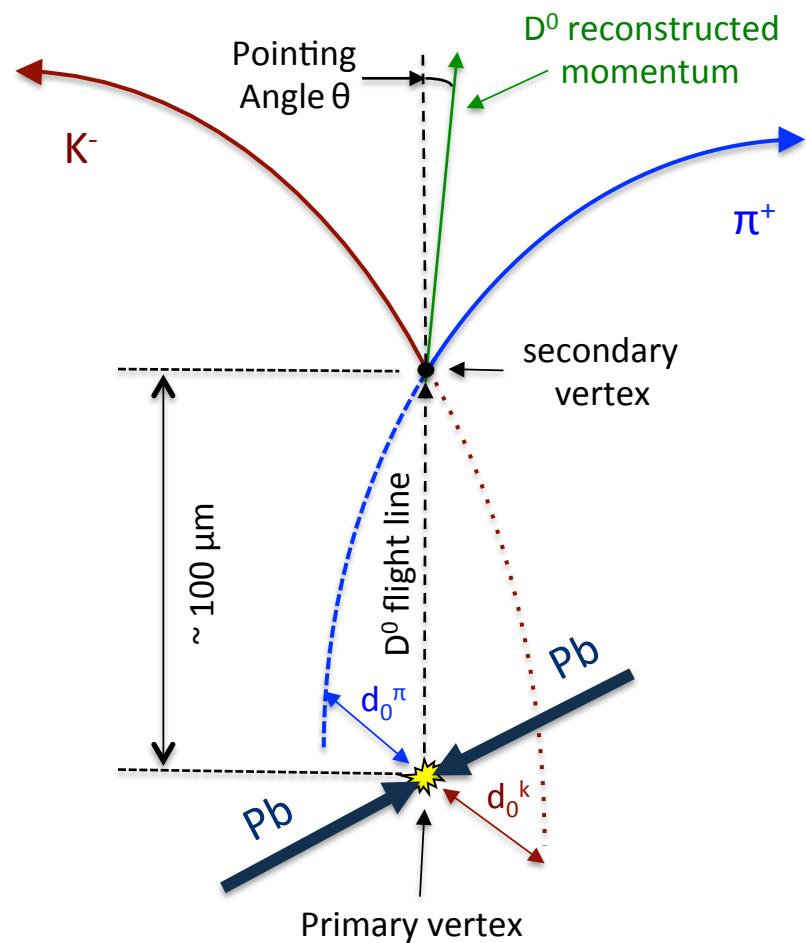
6 concentric barrels, 3 different technologies

- 2 layers of silicon pixel (SPD)
- 2 layers of silicon drift (SDD)
- 2 layers of silicon strips (SSD)



ITS – Secondary vertex determination

Example: D^0 meson



Open charm

| Particle | Decay Channel | $c\tau (\mu\text{m})$ |
|---------------|--------------------------|-----------------------|
| D^0 | $K^- \pi^+$ (3.8%) | 123 |
| D^+ | $K^- \pi^+ \pi^+$ (9.5%) | 312 |
| D_s^+ | $K^+ K^- \pi^+$ (5.2%) | 150 |
| Λ_c^+ | $p K^- \pi^+$ (5.0%) | 60 |

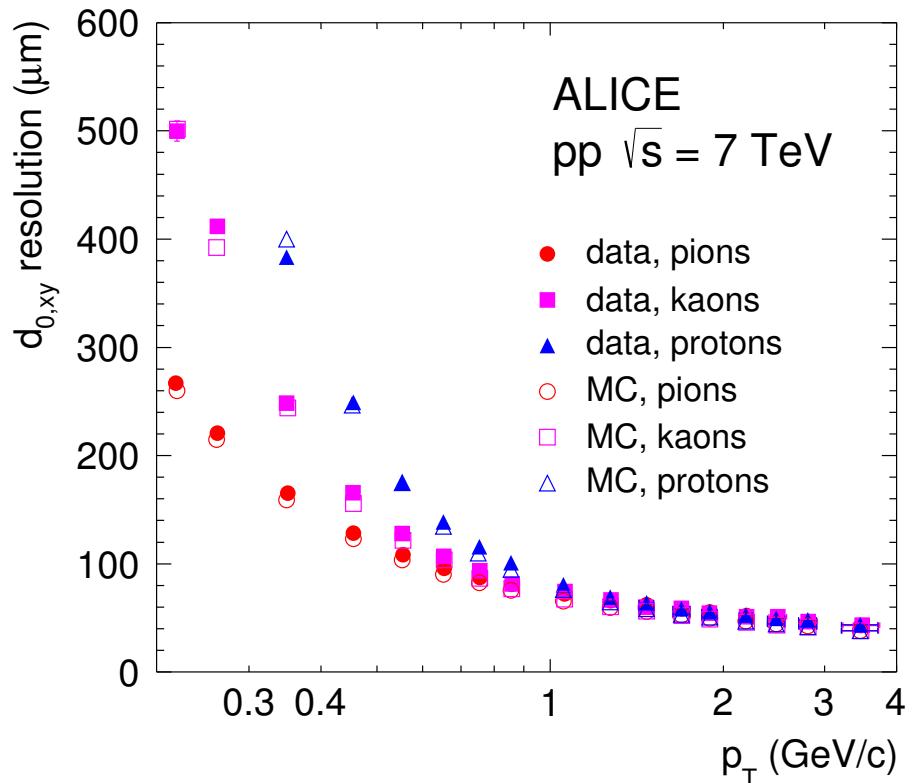
How precisely is d_0 measured with the current ITS detector?

Analysis based on decay topology and invariant mass technique

ALICE ITS Upgrade – Impact parameter resolution

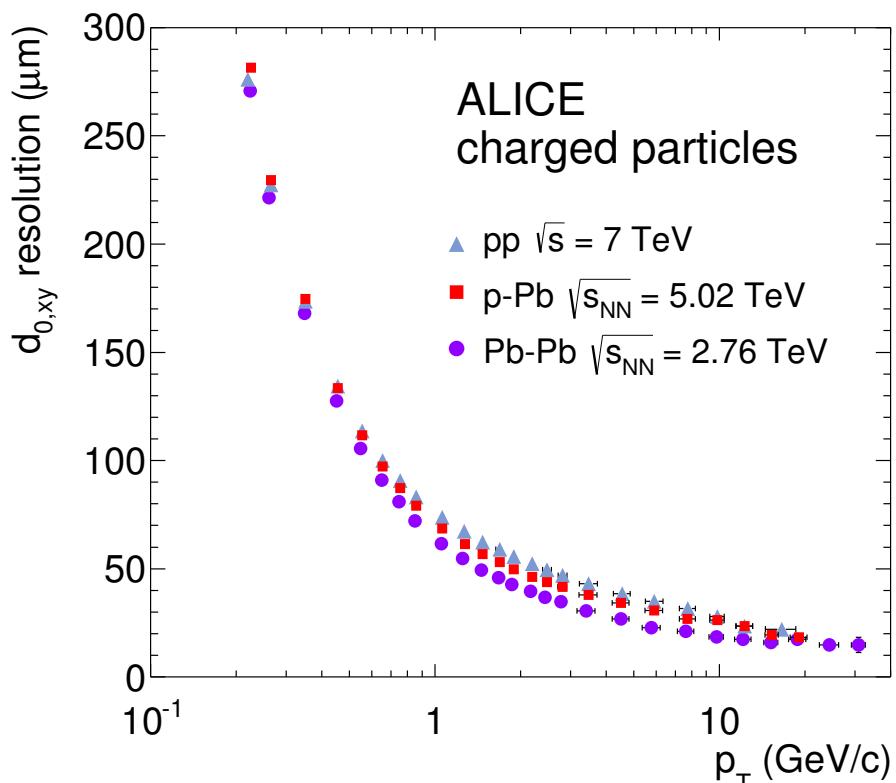


Very good MC description



ALICE, Int. J. Mod. Phys. A29 (2014) 1430044

Very weak dependence on the colliding system



ALICE, Int. J. Mod. Phys. A29 (2014) 1430044

70 μm at $p_T = 1$ GeV/c

Past

RUN1 (2010 - 2013)

| Year | System | Energy $\text{sqrt}(s_{\text{NN}})$ | Integrated lumin |
|------|--------|-------------------------------------|-----------------------------|
| 2010 | Pb-Pb | 2.76 TeV | $\sim 0.01 \text{ nb}^{-1}$ |
| 2011 | Pb-Pb | 2.76 TeV | $\sim 0.1 \text{ nb}^{-1}$ |
| 2013 | p-Pb | 5.02 TeV | $\sim 30 \text{ nb}^{-1}$ |

Present and near future

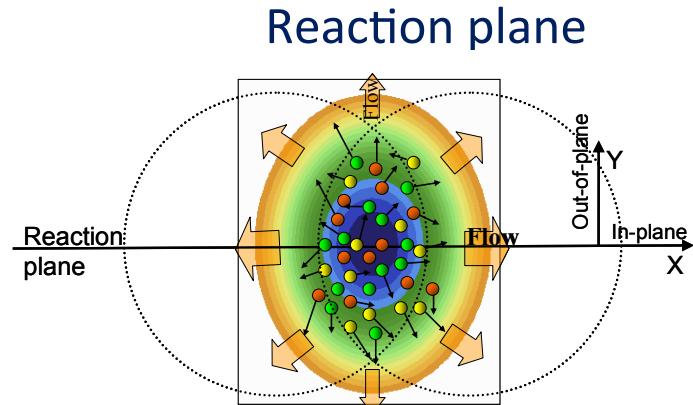
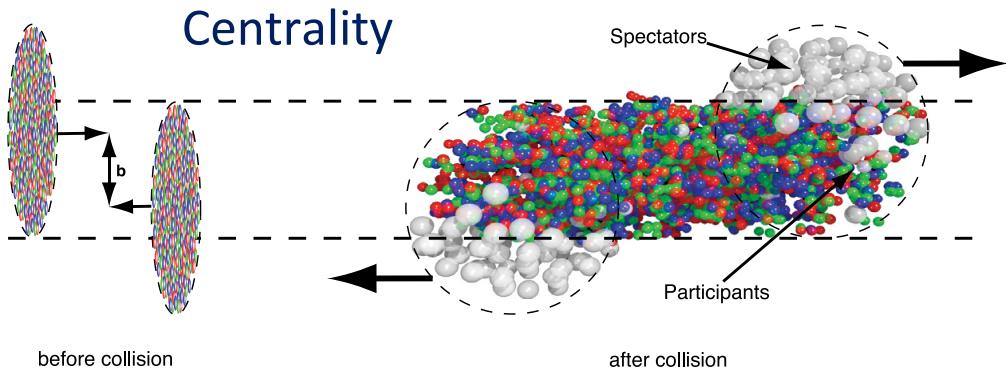
RUN2 (2015 - 2018)

- 1nb^{-1} for Pb-Pb collisions, with improved detectors and double energy

ALICE: study QGP properties

Progress on the characterization of QGP properties

- precision measurements of **rare probes**
- over a large kinematic range (from high to very low transverse momenta)
- and as function of multi-differential observables: centrality, reaction plane, ...



One example:

precision measurements of spectra, correlations and flow of heavy flavour hadrons and quarkonia at **low transverse momenta** (**not possible to trigger!!**)

This requires statistics (luminosity) and precision measurements

Target for **upgrade programme** (Run3 + Run4)

- Pb-Pb recorded luminosity $\geq 10 \text{ nb}^{-1}$ $\rightarrow 8 \times 10^{10}$ events

I. Upgrade detectors, readout systems and online systems to

- read out all Pb-Pb interactions at a maximum rate of 50kHz (i.e. $L = 6 \times 10^{27} \text{ cm}^{-2}\text{s}^{-1}$), with a minimum bias trigger (at present 500Hz)
→ Gain a factor **100** in statistics over originally approved programme (Run1 + Run2)

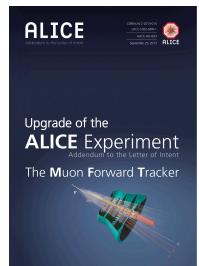
II. Significant improvement of vertexing and tracking capabilities at low p_T

- **New Inner tracking System**

It targets LHC 2nd Long Shutdown (2018/19)

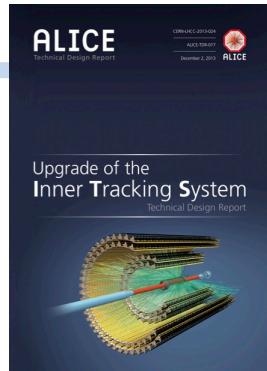


ALICE Upgrade LoI
September 2012



Addendum
September 2013

ITS upgrade design objectives



CERN-LHCC-2013-24

1. Improve impact parameter resolution by a factor of ~ 3

- Get closer to IP (position of first layer): 39mm \rightarrow 23mm
- Reduce x/X_0 /layer: $\sim 1.14\%$ $\rightarrow \sim 0.3\%$ (for inner layers)
- Reduce pixel size: currently $50\mu\text{m} \times 425\mu\text{m}$ $\rightarrow O(30\mu\text{m} \times 30\mu\text{m})$

2. Improve tracking efficiency and p_T resolution at low p_T

- Increase granularity:
 - 6 layers \rightarrow 7 layers
 - silicon drift and strips \rightarrow pixels

3. Fast readout

- readout Pb-Pb interactions at > 100 kHz and pp interactions at \sim several 10^5 Hz (currently limited at 1kHz with full ITS)

J. Phys. G (41) 087002

4. Fast insertion/removal for yearly maintenance

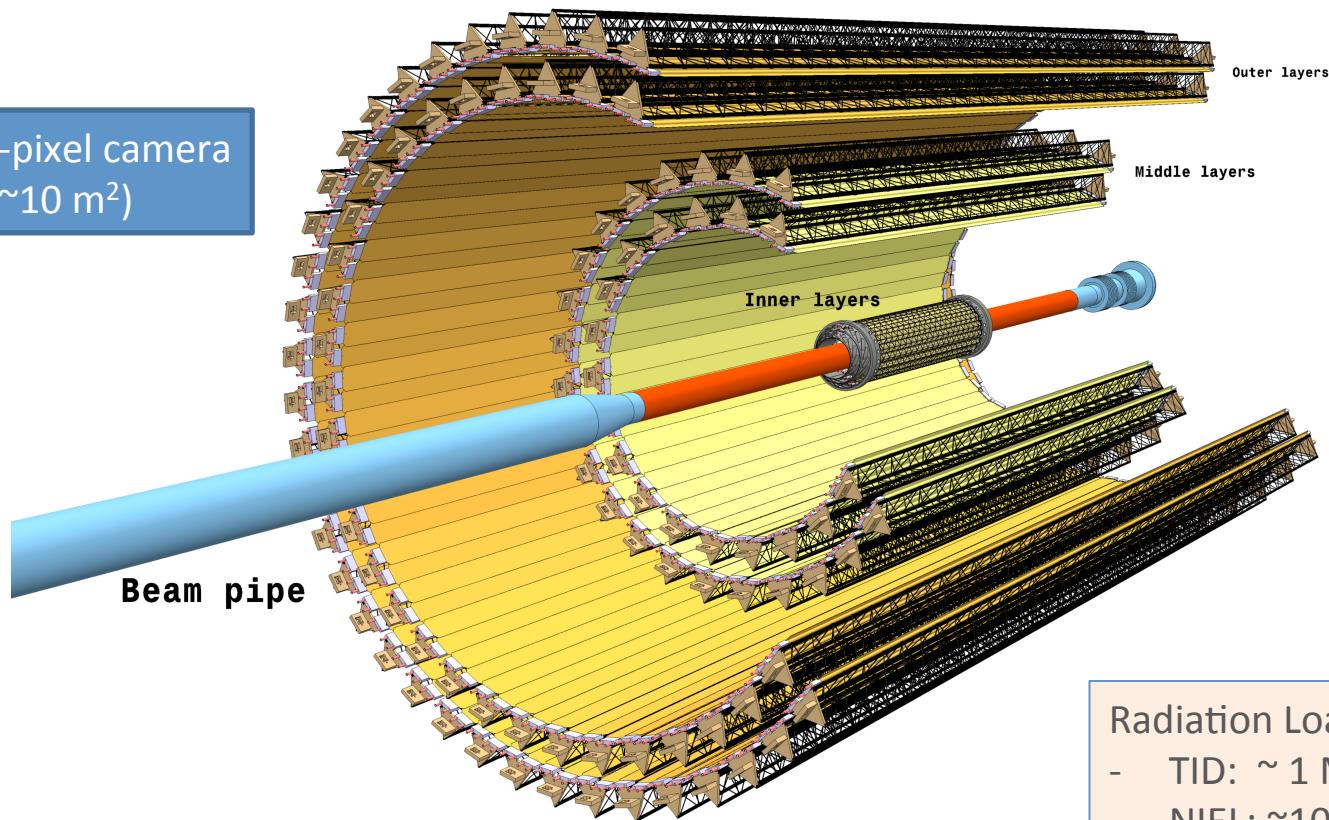
- possibility to replace non functioning detector modules during yearly shutdown

Install detector during LHCC LS2 (2018-19)



New ITS Layout

12.5 G-pixel camera
(~10 m²)



7-layer barrel geometry based on MAPS

r coverage: 23 – 400 mm

η coverage: $|\eta| \leq 1.22$
for tracks from 90% most luminous region

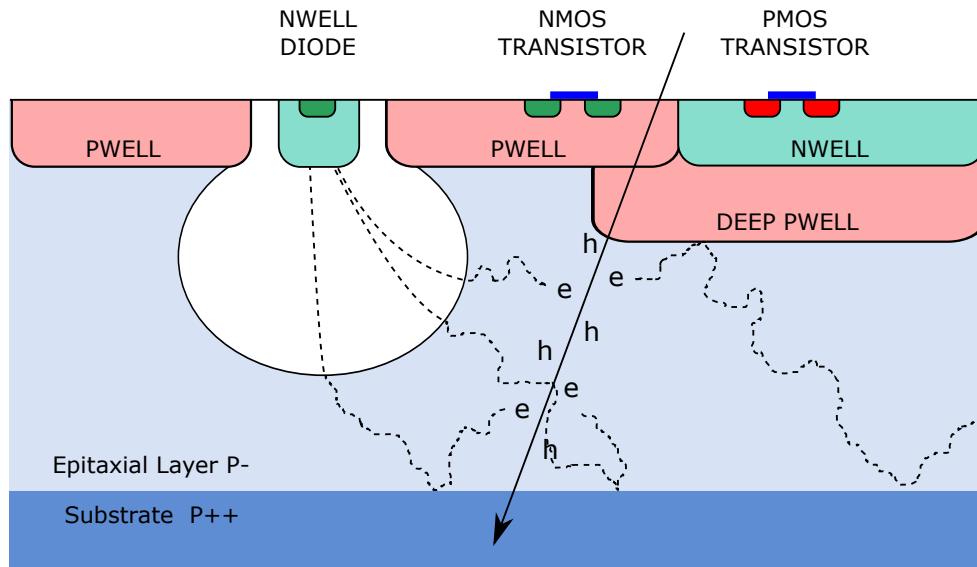
3 Inner Barrel layers (**IB**)

4 Outer Barrel layers (**OB**)

Material /layer : 0.3% X₀ (IB), 1% X₀ (OB)

ITS Pixel Chip – technology choice

CMOS Pixel Sensor using TowerJazz 0.18μm CMOS Imaging Process



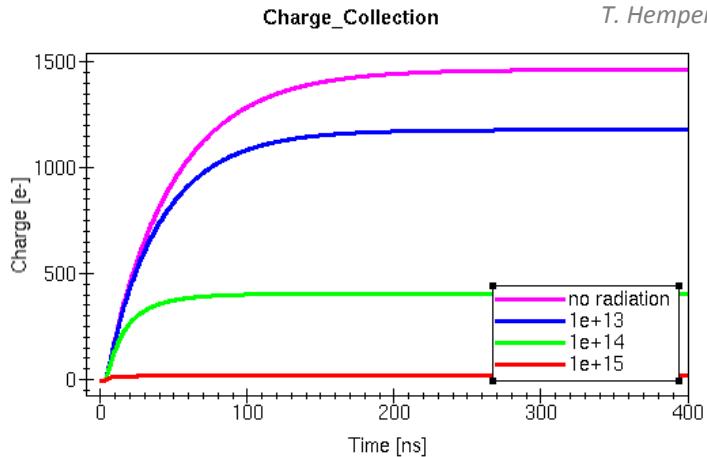
Tower Jazz 0.18 μm CMOS

- feature size 180 nm
- metal layers 6
- ➔ Suited for high-density, low-power
- Gate oxide 3nm
- ➔ Circuit rad-tolerant

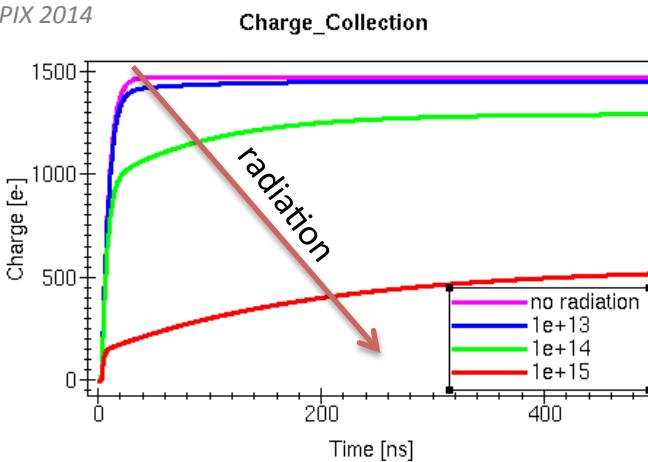
- ▶ High-resistivity ($> 1\text{k}\Omega \text{ cm}$) p-type epitaxial layer (20 μm - 40 μm thick) on p-type substrate
- ▶ Small n-well diode (2-3 μm diameter), ~ 100 times smaller than pixel => low capacitance
- ▶ Application of (moderate) reverse bias voltage to substrate can be used to increase depletion zone around NWELL collection diode
- ▶ Quadruple well process: deep PWELL shields NWELL of PMOS transistors, allowing for full CMOS circuitry within active area

ITS Pixel Chip – starting material

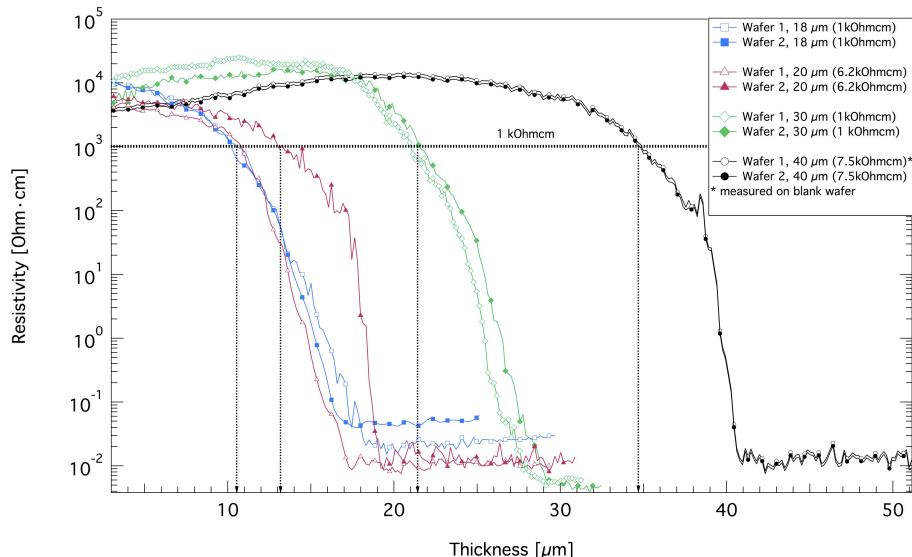
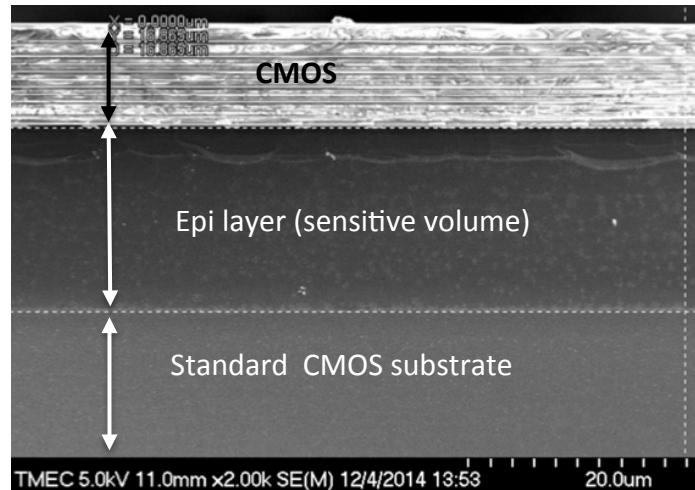
Charge collection time and recombination depend on doping concentration (Si resistivity) and radiation induced dislocations



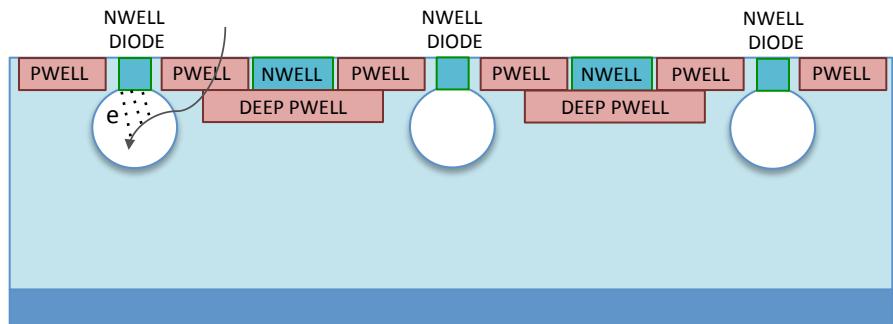
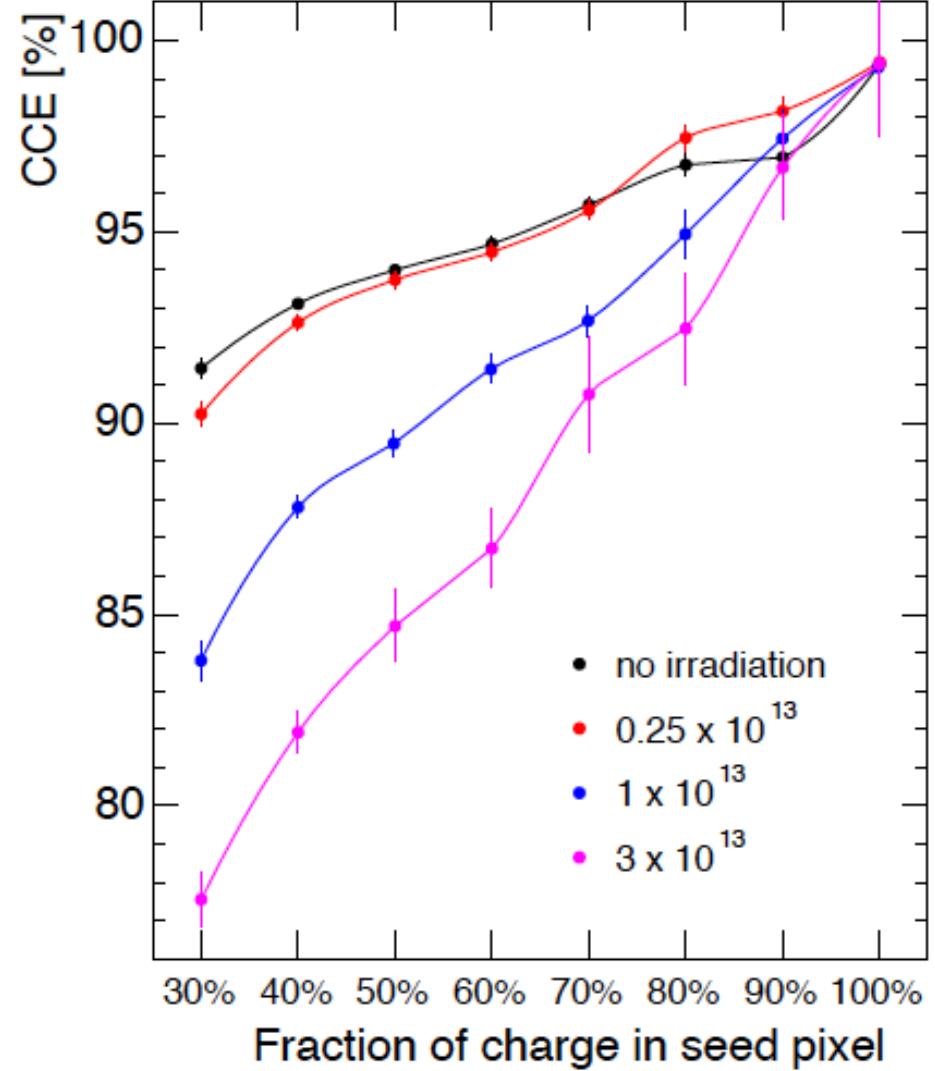
Substrate: 10 Ohm cm, NWELL: @1V PW: @ 0V



Substrate: 2k Ohm cm, NWELL: @1V PW: @ 0V

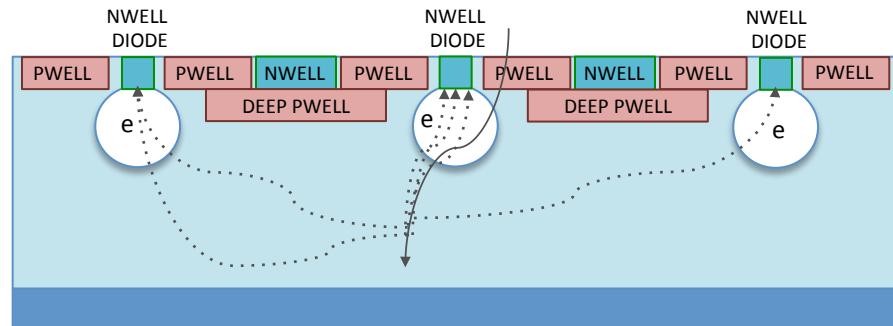


ITS Pixel Chip – charge recombination



^{55}Fe X-ray absorption close to collection diode

- small diffusion => small recombination
- Signal collected in a single pixel

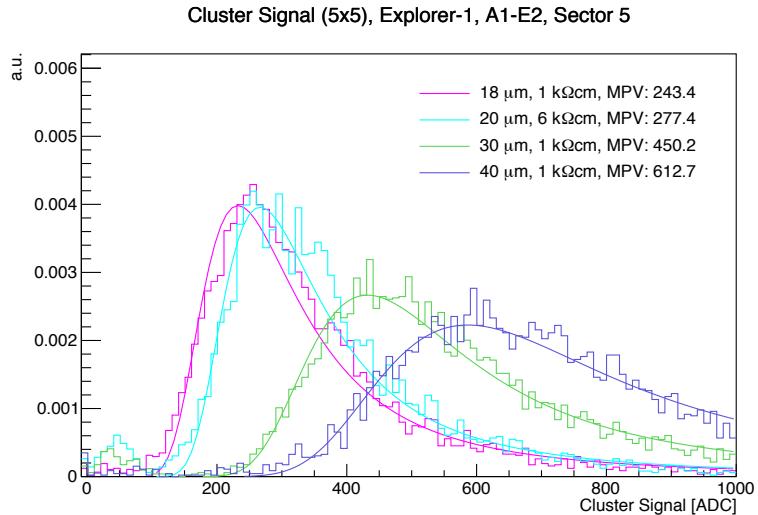


^{55}Fe X-ray absorption far from collection diode

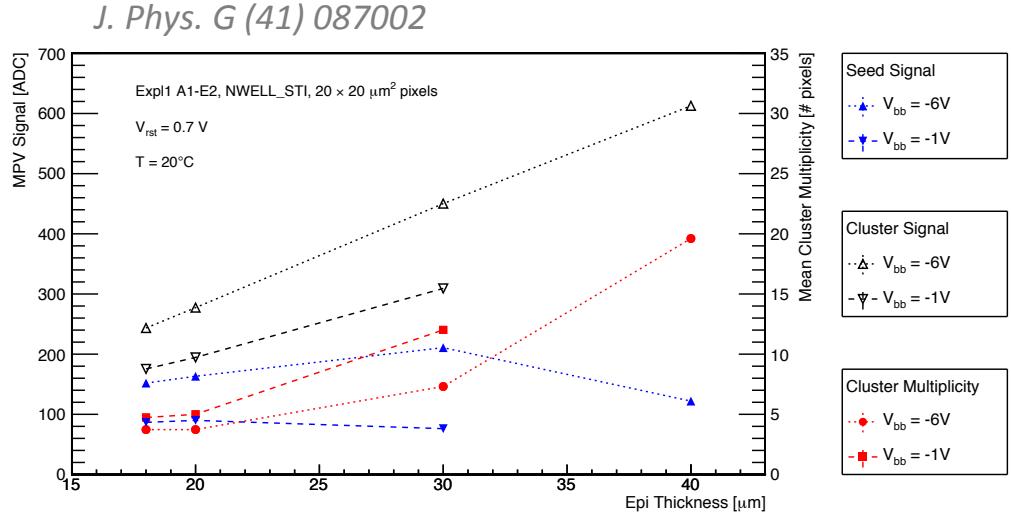
- large diffusion => large recombination
- signal spreads over several pixels

ITS Pixel Chip – starting material

Thicker epitaxial layers will yield more charge but ... diffusion increases cluster size



J. Van Hoorne, TIPP2014



Measurements done at Desy test beam with 3.2 Gev/c positrons

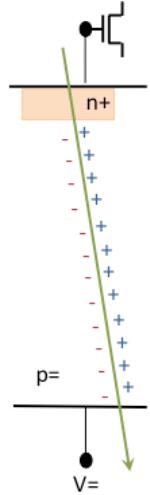
- Cluster charge increases linearly with epi-layer thickness
- Cluster size increases with epi-layer thickness

optimum epi thickness (maximum seed signal) increases by increasing depletion volume

ITS Pixel Chip – starting material

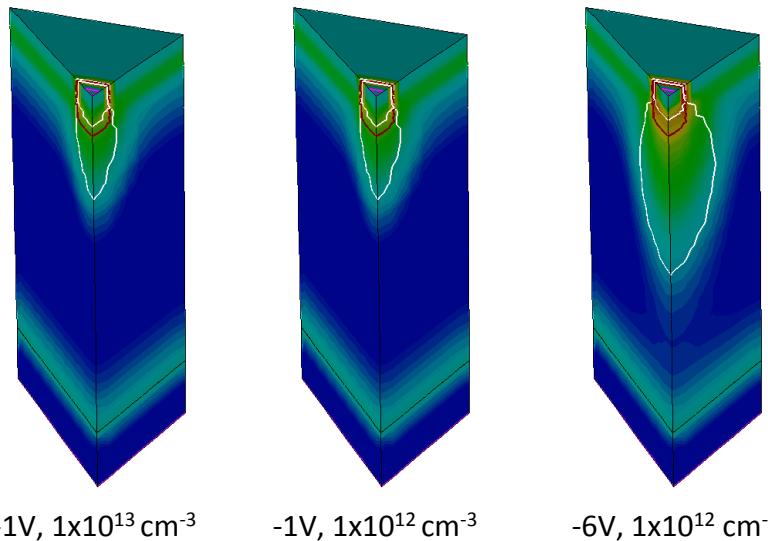
Low input capacitance decisive to achieve large S/N at low power

(W. Snoeys, NIMA 731 (2013) 125-130)



NWELL DIODE output signal = Q / C

- Minimize spread of charge over many pixels
- minimize capacitance:
 - ➡ small diode surface
 - ➡ large depletion volume

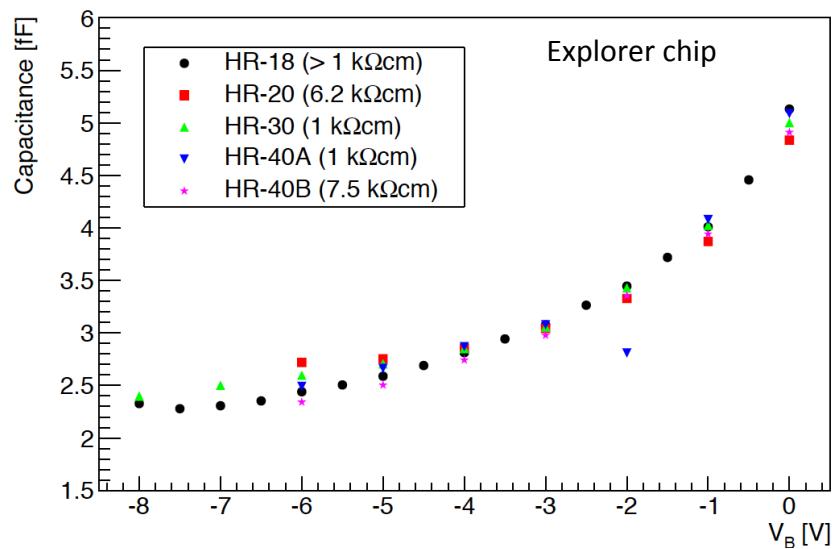


-1V, $1 \times 10^{13} \text{ cm}^{-3}$

-1V, $1 \times 10^{12} \text{ cm}^{-3}$

-6V, $1 \times 10^{12} \text{ cm}^{-3}$

Diode $3\mu\text{m} \times 3\mu\text{m}$ square n-well , White line: boundaries of depletion region



- ☞ Pixel input capacitance decreases with increasing reverse bias, in agreement with simulated size of depletion region
- ☞ Minor influence of epi resistivity for current pixel layout

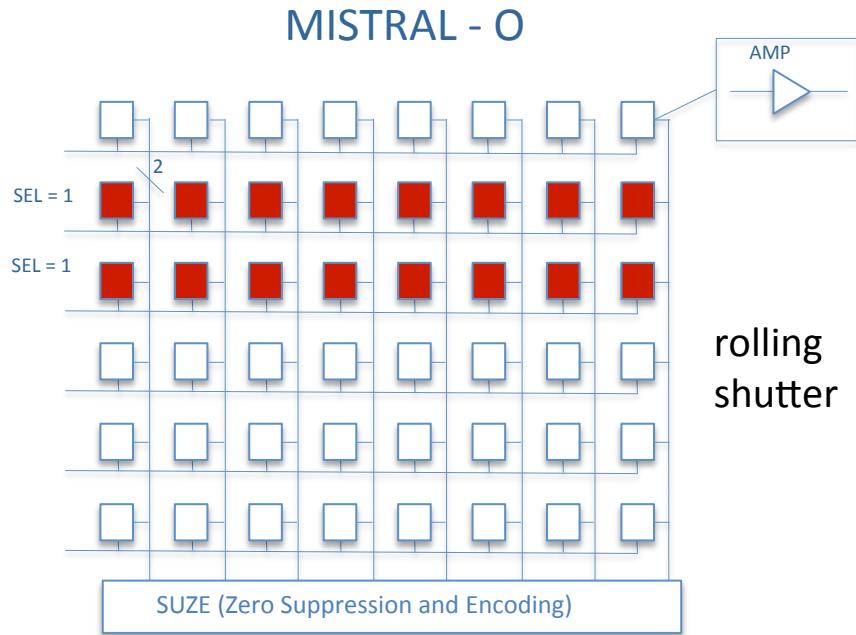
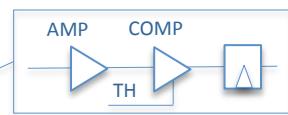
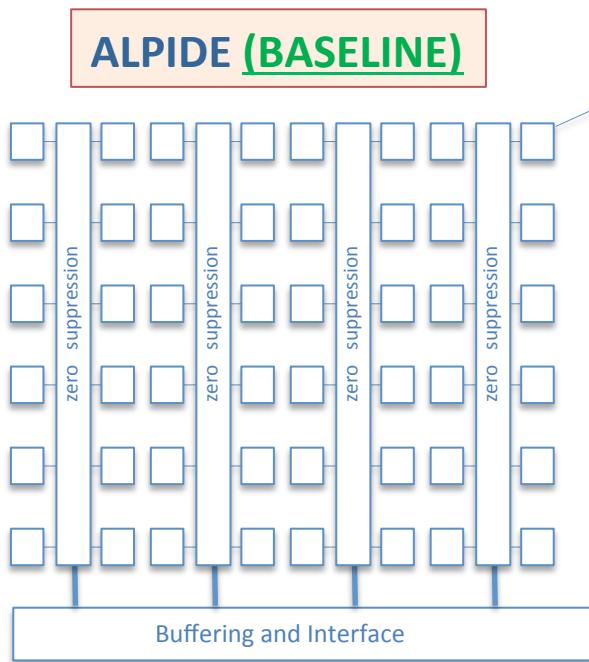
PIXEL Chip – General Requirements



| Parameter | Inner Barrel | Outer Barrel |
|-----------------------------|--|---|
| Silicon thickness | | 50 μm |
| Spatial resolution | 5 μm | 10 μm |
| chip dimensions | | 15 mm \times 30 mm |
| Power density | < 300 mW/cm ² | < 100 mW/cm ² |
| Event time resolution | | < 30 μs |
| Detection efficiency | | > 99% |
| Fake hit rate | | < 10 ⁻⁵ per readout frame |
| TID radiation hardness (*) | 2700 krad | 100 krad |
| NIEL radiation hardness (*) | 1.7x10 ¹³ 1MeV n _{eq} /cm ² | 10 ¹² 1MeV n _{eq} / cm ² |

(*) 10 x radiation load integrated over approved programme (\sim 6 years of operation)

ITS Pixel Chip – two architectures



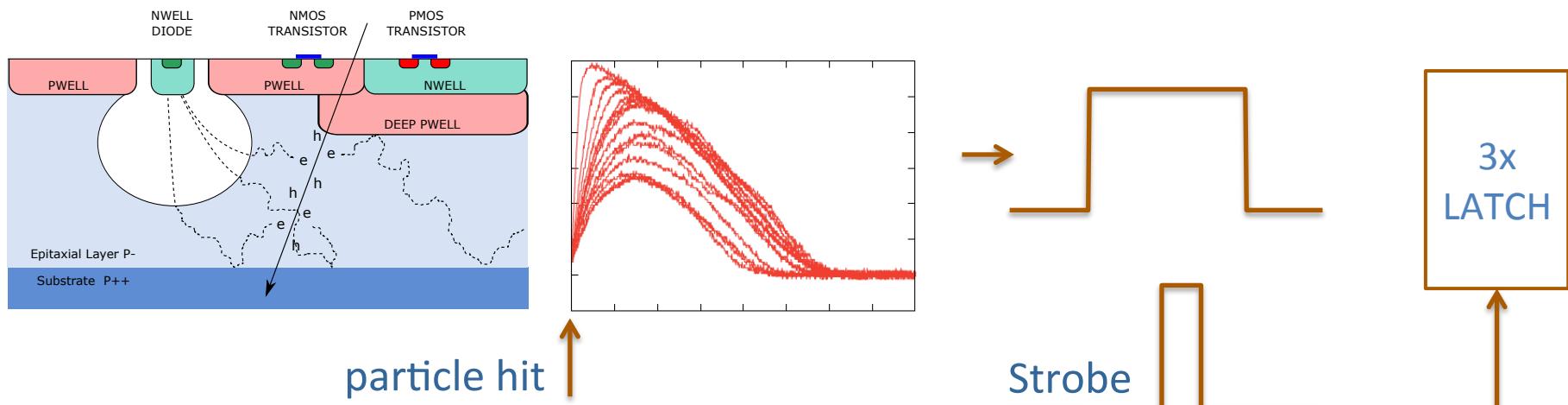
| | |
|-----------------------|--------------------------------------|
| Pixel pitch | $28\mu\text{m} \times 28\mu\text{m}$ |
| Event time resolution | $<2\mu\text{s}$ |
| Power consumption | 39mW/cm^2 |
| Dead area | 1.1 mm x 30mm |

| | |
|----------------------------------|--------------------------------------|
| Pixel pitch | $36\mu\text{m} \times 64\mu\text{m}$ |
| Event time resolution | $\sim 20\mu\text{s}$ |
| Power consumption ^(*) | 97mW/cm^2 |
| Dead area | 1.7 mm x 30mm |

ALPIDE and MISTRAL-O have same dimensions (15mm x 30mm), identical physical and electrical interfaces: position of interface pads, electrical signaling, protocol

(*) might further reduce to 73mW/cm^2

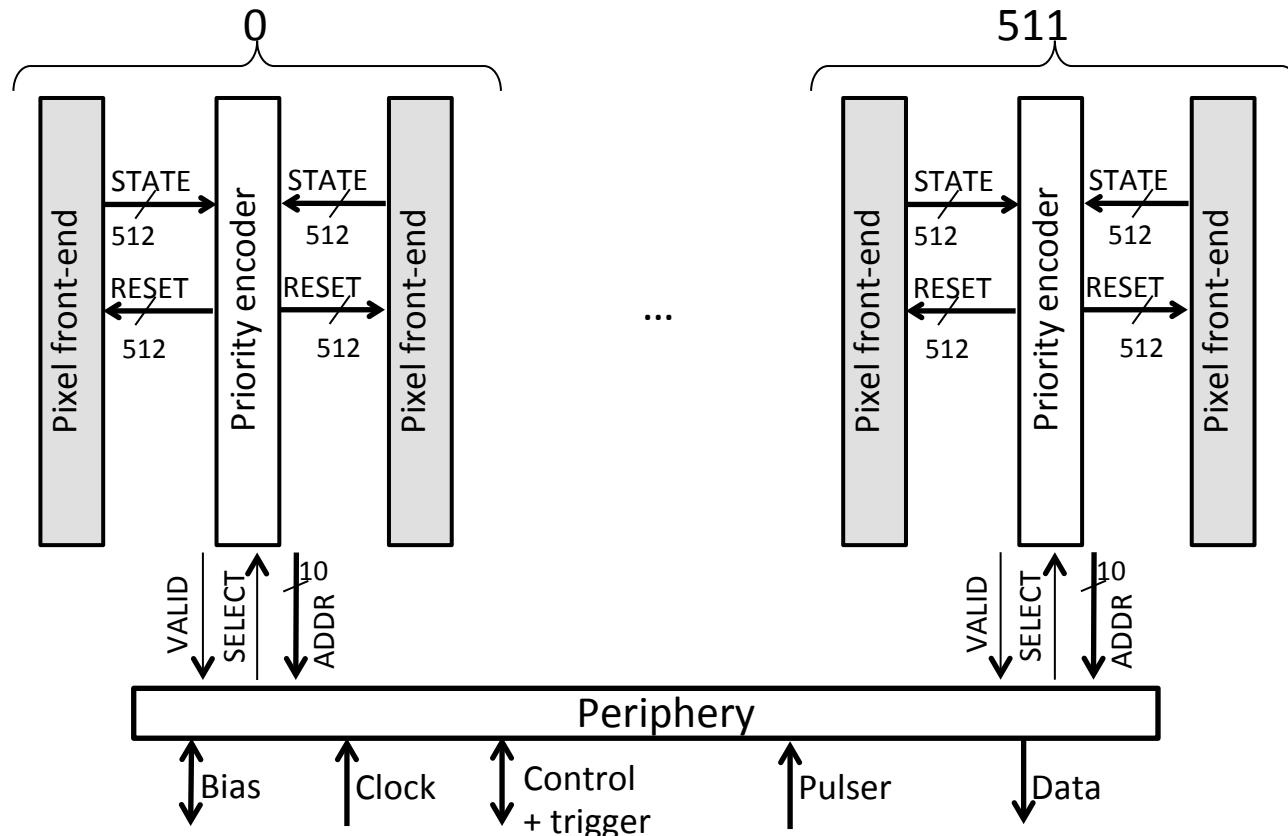
ALPIDE Principle of Operation



Front-end acts as a delay line

- Sensor and front-end continuously active
- Upon particle hit front end forms a pulse with $\sim 1\text{-}2 \mu\text{s}$ rise time
- Threshold is applied to form binary pulse
- Hit is latched into memory if strobe is applied during binary pulse

ALPIDE Principle of Operation



Hit driven architecture

- Priority encoder sequentially provides addresses of all hit pixels present in double column
- No activity if no hit → **low power**

pALPIDE-1 (May 2014) – first full-scale prototype

ALPIDE Full Scale prototype

- Dimensions: 30mm x 15 mm
- Pixel Matrix: 1024 cols x 512 rows
- Final pixel pitch: 28 μ m x 28 μ m
- Power consumption: < 40mW/cm²
- Interface pads over matrix
- 1 register/pixel, no final interface

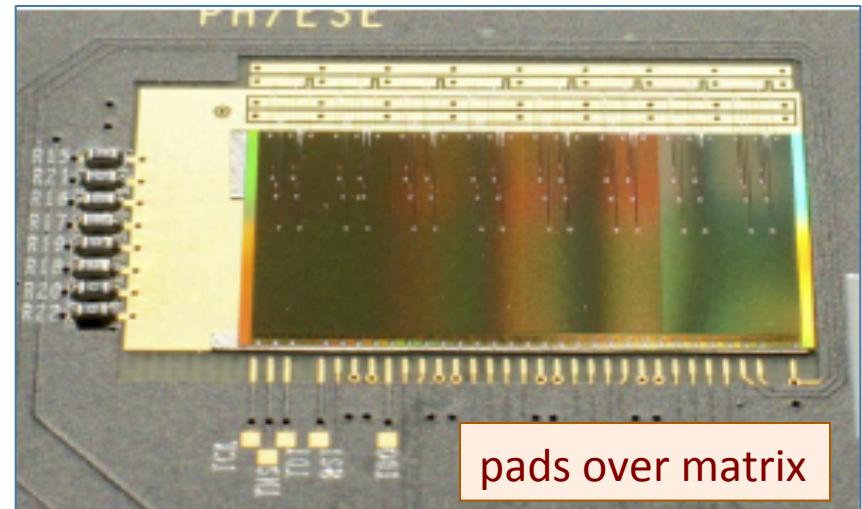
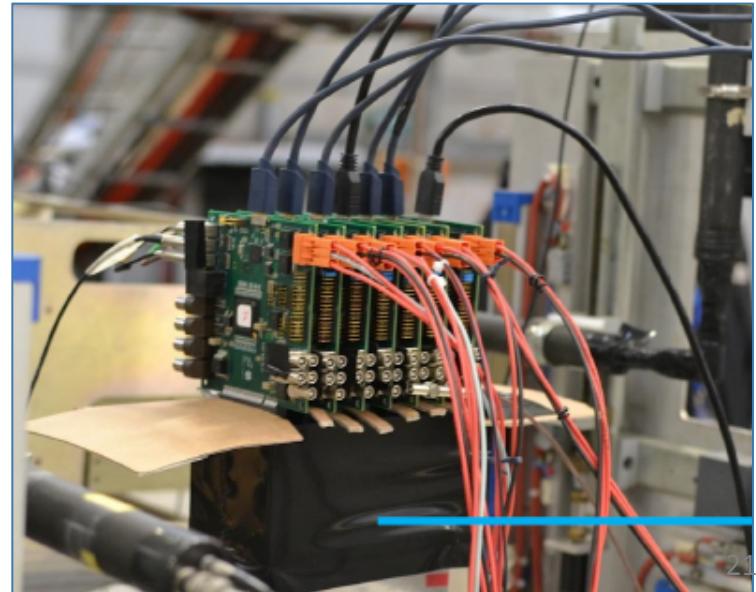
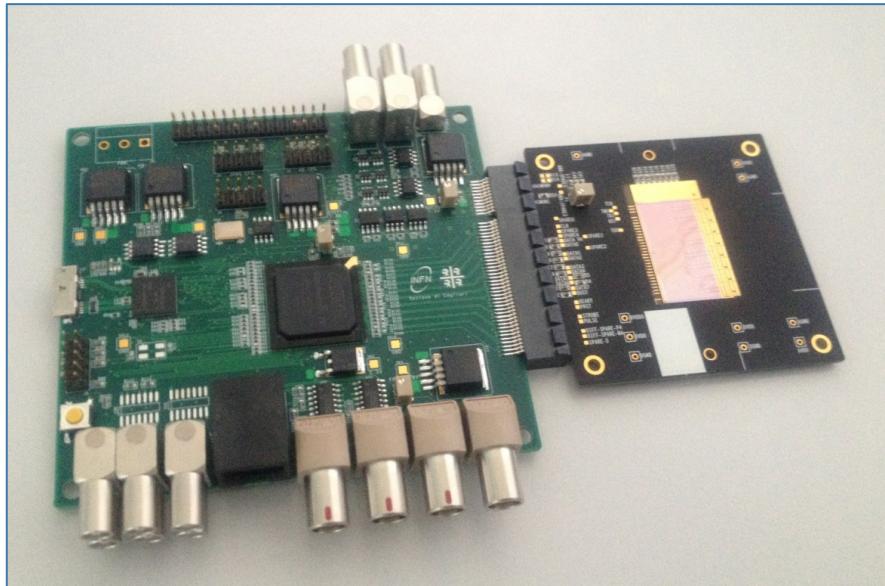
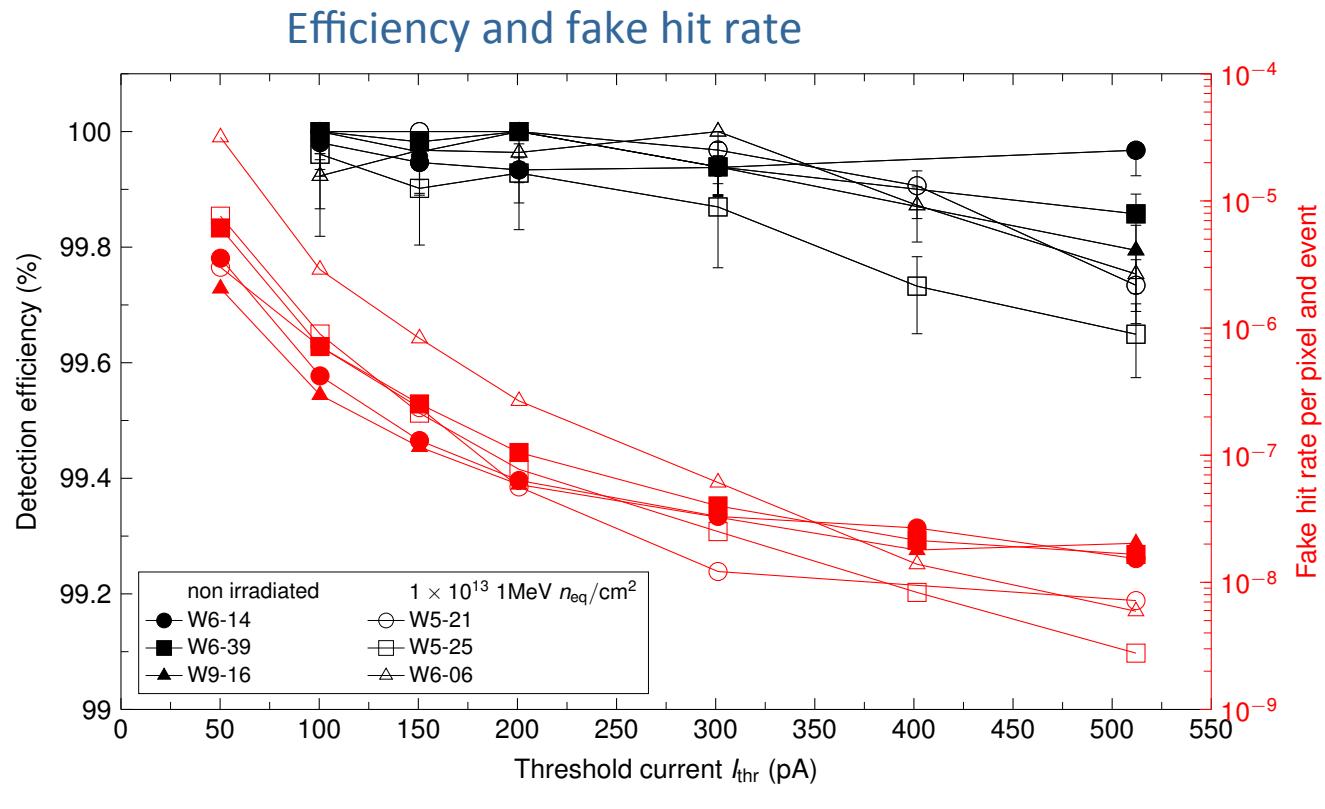


Figure: picture of pALPIDE-1

7-plane telescope based on pALPIDE-1 chip

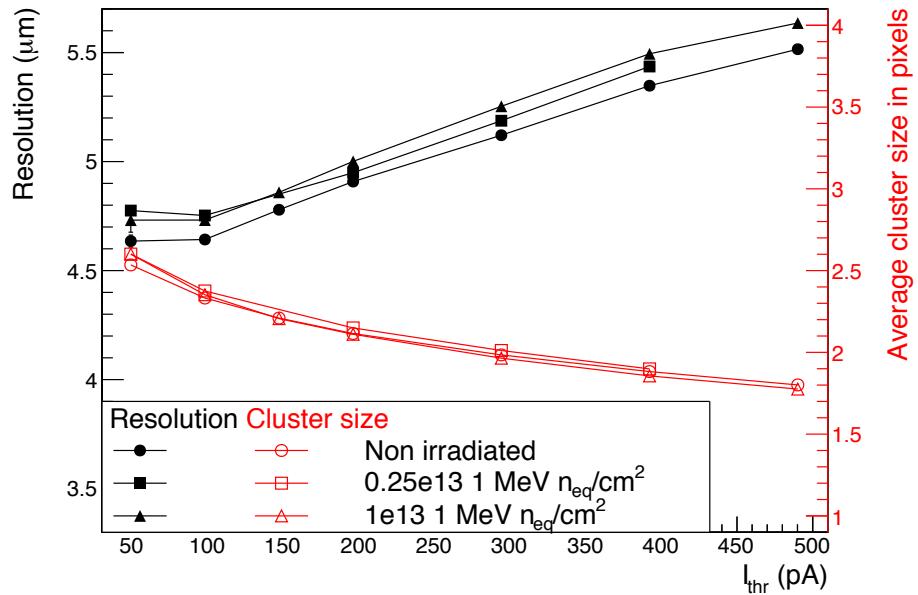




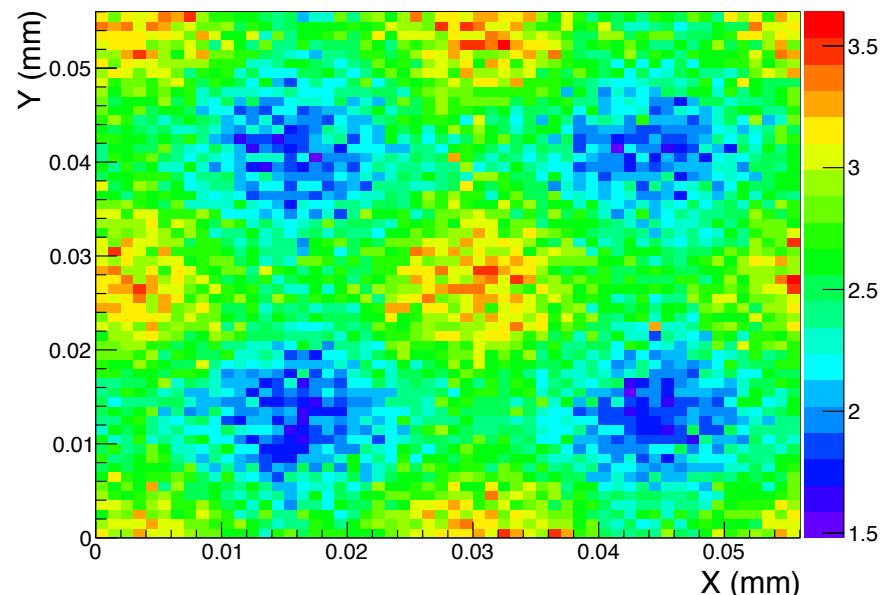
$\lambda_{\text{fake}} << 10^{-5} / \text{event/pixel} @ \epsilon_{\text{det}} > 99\% \rightarrow \text{very large margin over design requirements}$

- Measurements at PS: 5 – 7 GeV π^- December 2014
- Results refer to 50 μm thick chips: 3 non irradiated and 3 irradiated with neutrons at $10^{13} \text{ 1MeV } n_{\text{eq}} / \text{cm}^2$

Spatial resolution



Cluster size vs. position within pixel

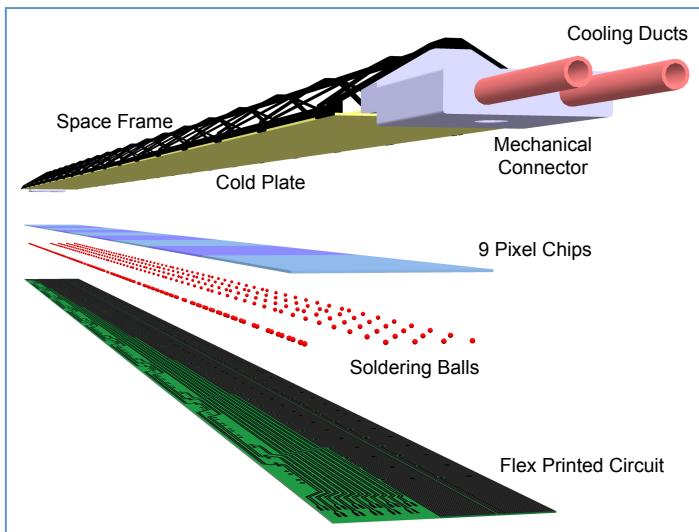


$\sigma_{\text{det}} \sim 5 \mu\text{m}$ is achieved with sufficient margin of operation

- Measurements at PS: 5 – 7 GeV π^- September 2014
- Results refer to 50 μm thick chips: non irradiated and irradiated with neutrons 0.25×10^{13} and $1 \times 10^{13} \text{ 1MeV } n_{\text{eq}} / \text{cm}^2$

p-ALPIDE-2: 2nd full-scale prototype

- Final I/O interface but ...NO high-speed output link (1.2 Gbit/sec replaced by a 40Mb/s)
- It allows full Integration in IB and OB Module (main focus in 2015)
- Delivery: April 2015
- Preliminary results show chip works according to specs



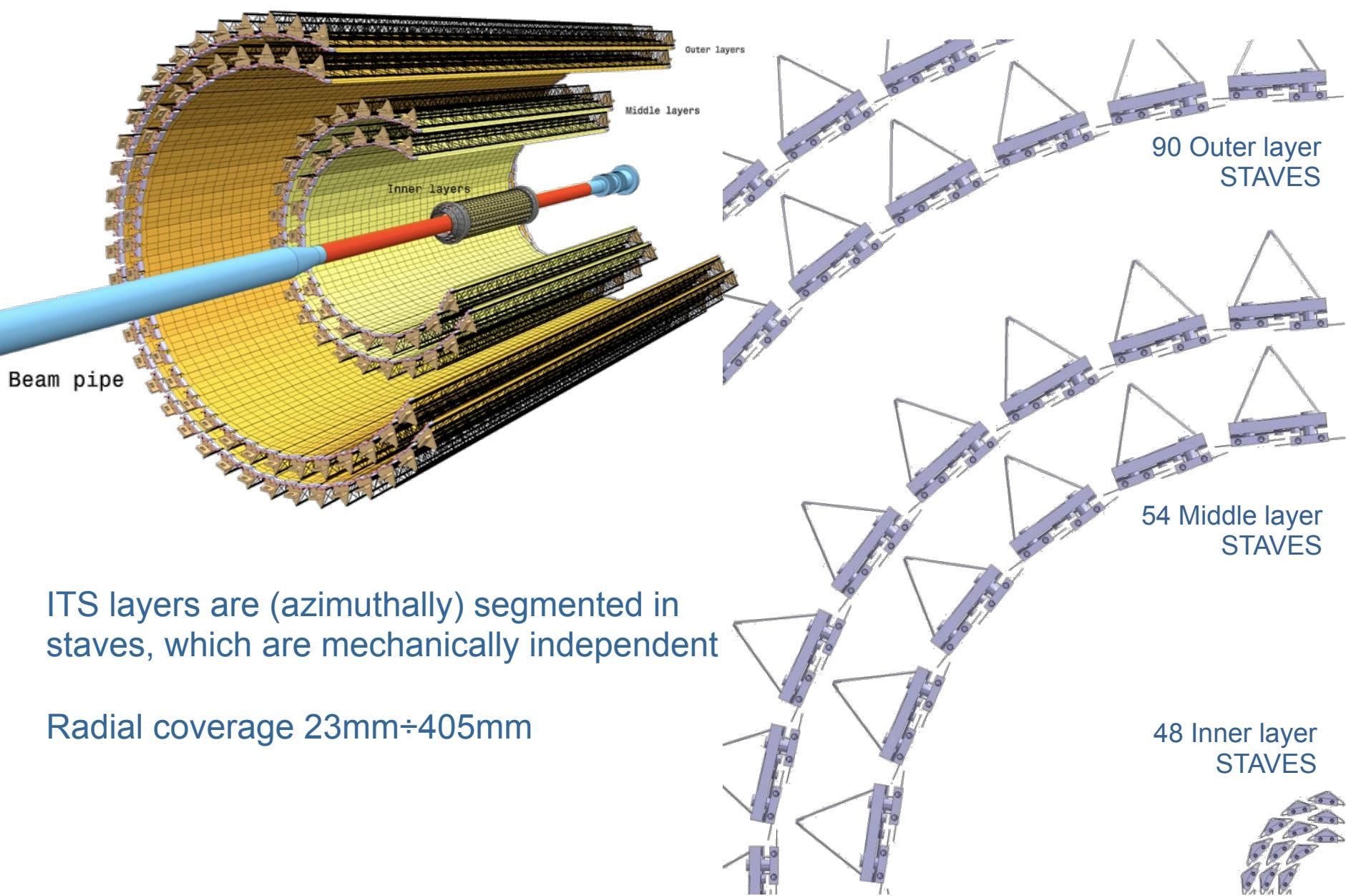
p-ALPIDE-3: 3rd full-scale prototype

- Contains all final elements
- Submission: wk 23 (1 Jun) Delivery: Aug '15

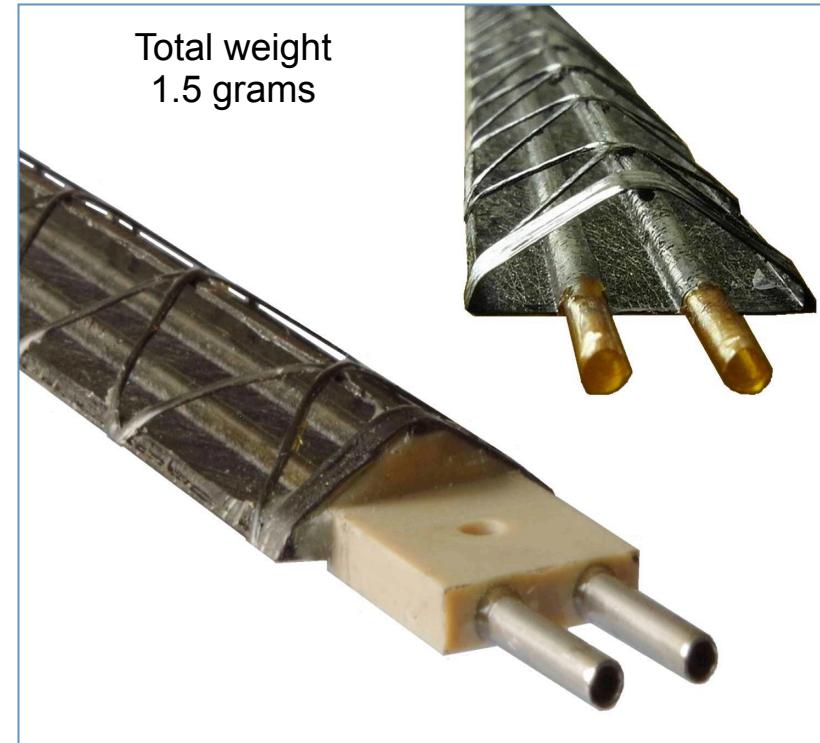
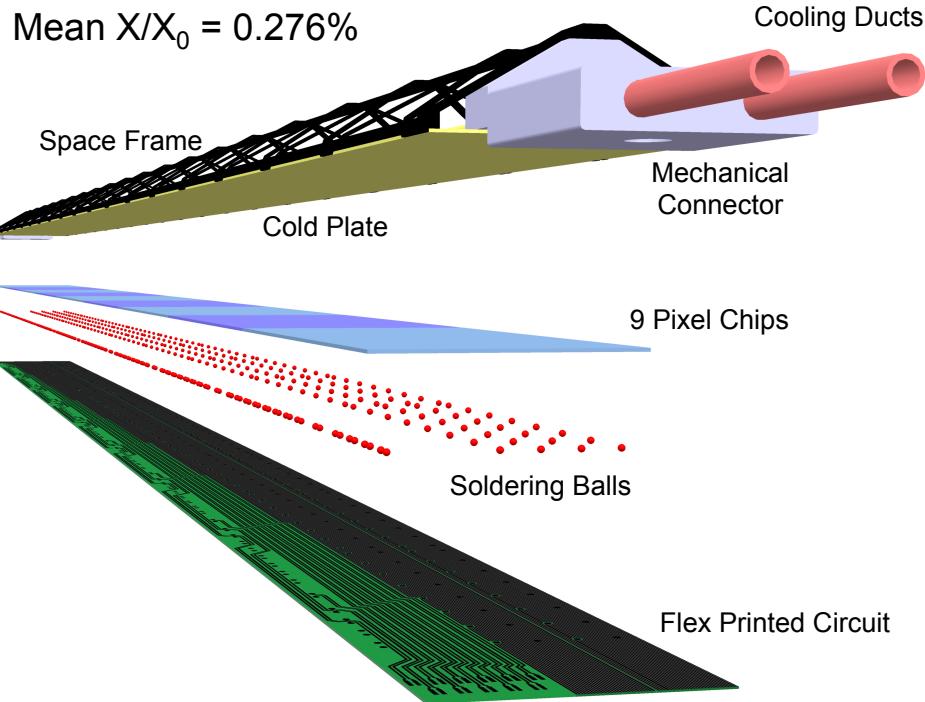
ALPIDE: pre-series production

- Submission Dec '15

New ITS layout



New ITS Layout - Inner Barrel Stave



$\langle \text{Radius} \rangle$ (mm): 23,31,39

Nr. of staves: 12, 16, 20

Nr. of chips/layer: 108, 144, 180

Power density: < 100 mW/cm²

Length in z (mm): 290

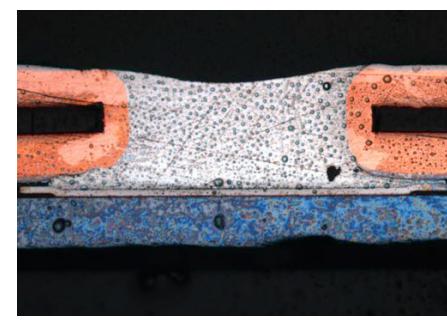
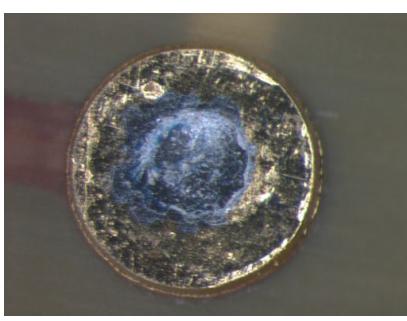
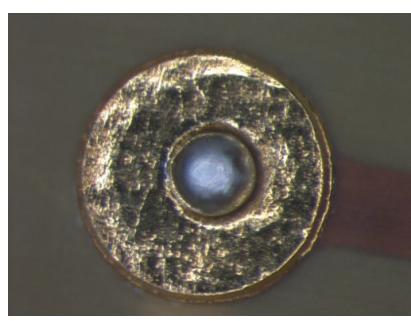
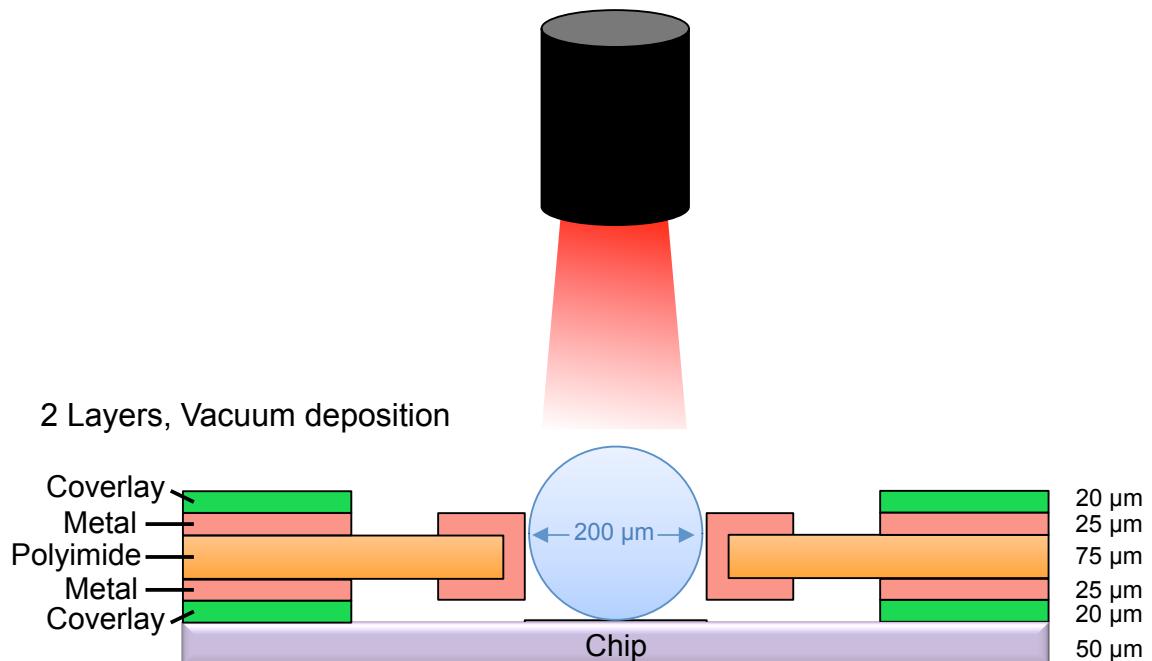
Nr. of chips/stave: 9

Material thickness: ~ 0.3% X_0

Throughput (@100kHz): < 80 Mb/s × cm⁻²

Interconnection of pixel chip to flex PCB

Laser soldering: Interconnection of Pixel chip on flexible printed circuit



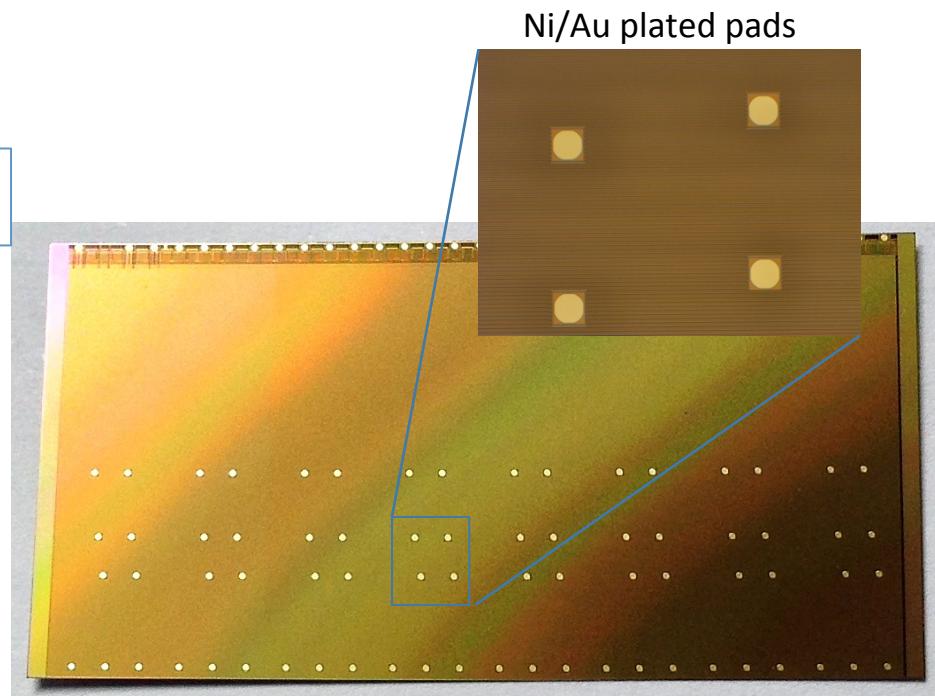
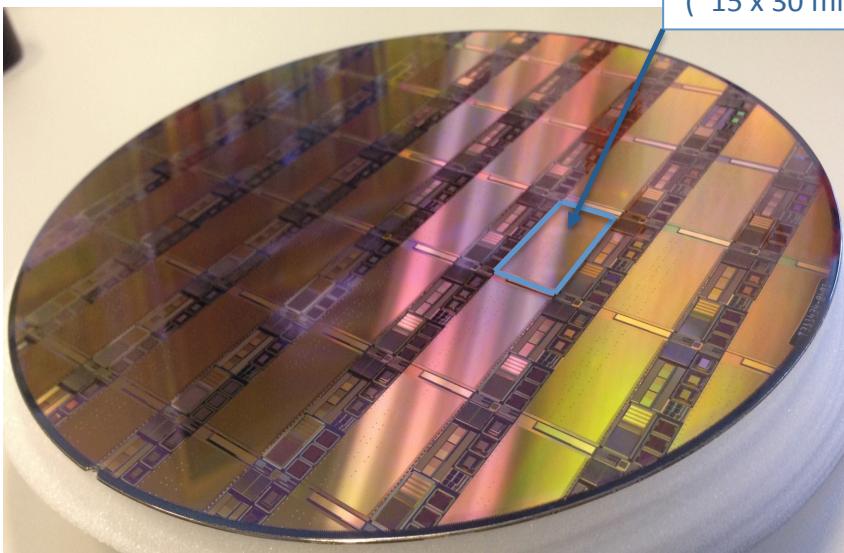
Solder Pads

- to solder the chip on the FPC, Al pads need Ni-Au plating (wet-able surface)
- plating is done on wafer using electroless Ni-Au plating, prior to thinning and dicing
- R&D experience 2012-now: plating of about 50 wafers (pad wafers and CMOS wafers)

Status

Market survey concluded

Tendering starting soon



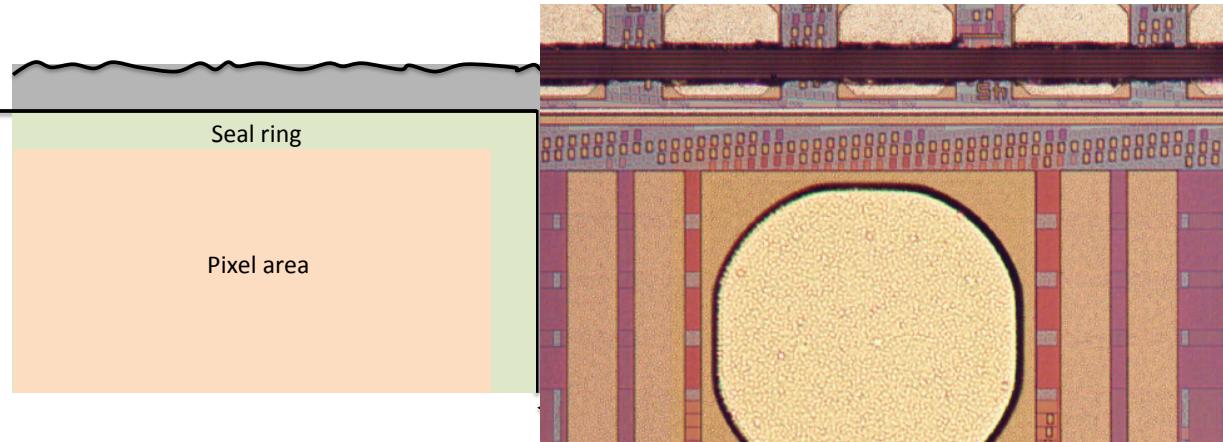
Contact pads are distributed over the matrix
(custom designed)

Pixel chip - thinning & dicing

- Diamond wheel pre-dice before grind (DBG) → extended experience (all types of wafers) with Rockwood (France)
- Main challenge: picking of large dies after dicing and grinding (50 μ m thick chip)
→ Development of special tools/procedures

Requirements

- Max. extension from the sealring:
25 μ m
- Chipout/cracks contained within
25 μ m extension region
- No cracks or chip outs touch the
seal ring
- Thickness variation: (50 \pm < 5) μ m



Experience (DBG) with blanks, pad wafers and fully processed CMOS wafers

Experience to handle large dies (pALPIDEfs)

✓ 90 wafers diced and thinned to 50 μ m

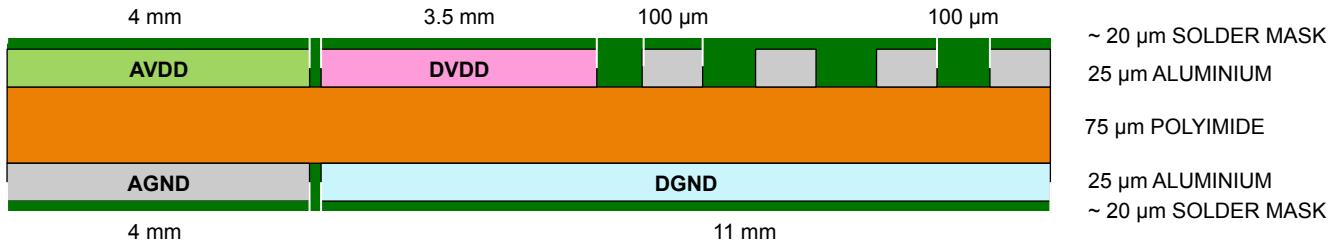
Status

Market survey in preparation, will be followed by tender in late summer 2015

Inner Barrel Stave – flexible printed circuit

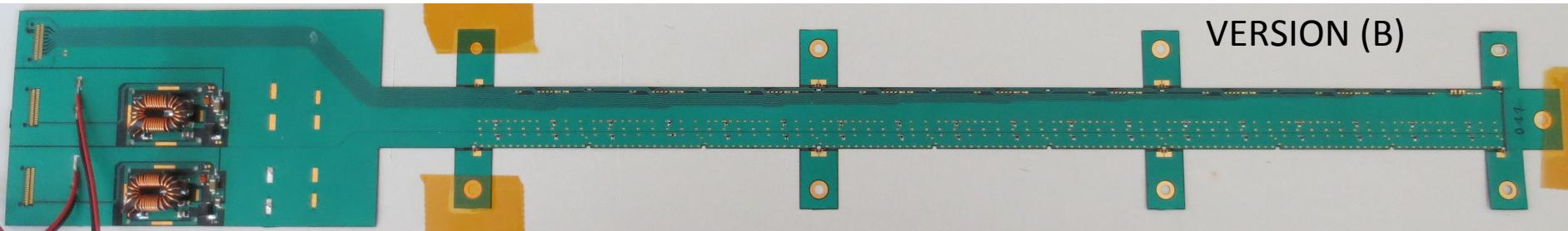
IB Flexible Printed Circuit prototypes (Al power planes and signal tracks)

Metallised vias of
220 μ m diameter

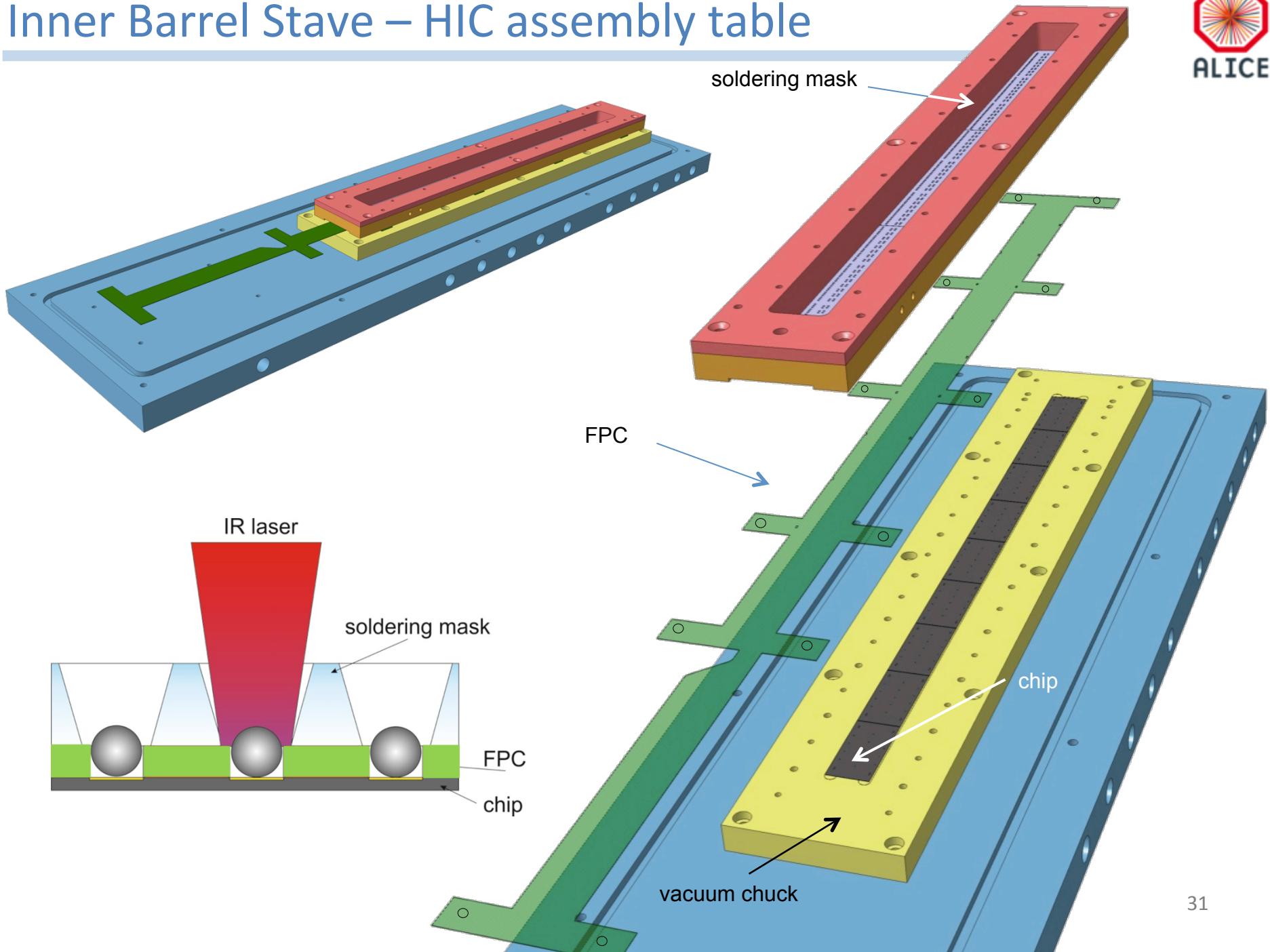


Status

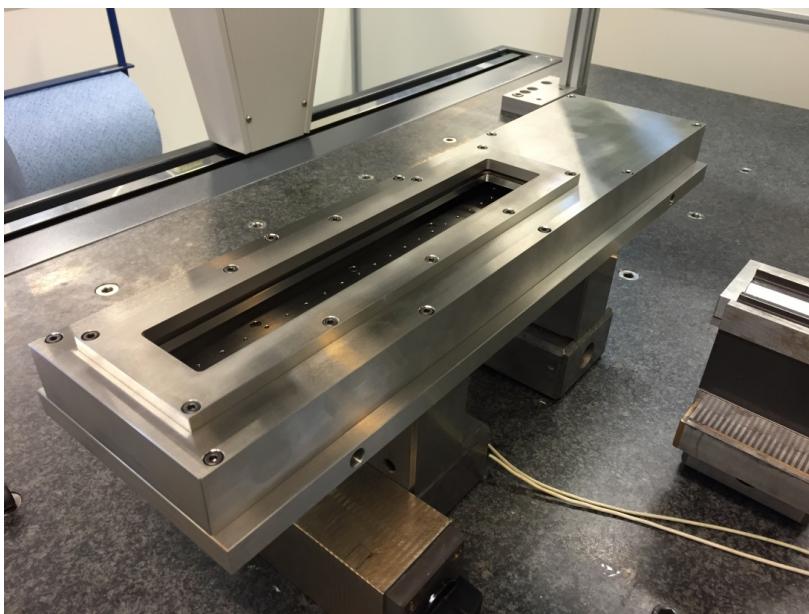
Two FPC versions (differ for the location of DC-DC converters)
ready to be tested with ALPIDE-2



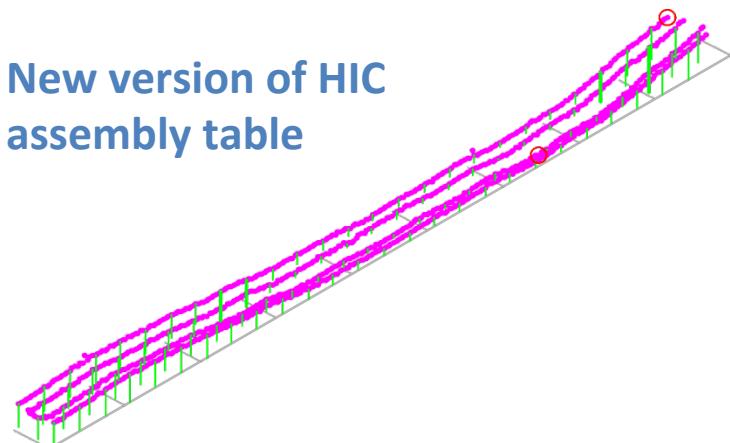
Inner Barrel Stave – HIC assembly table



New ITS Layout - Inner Barrel Stave

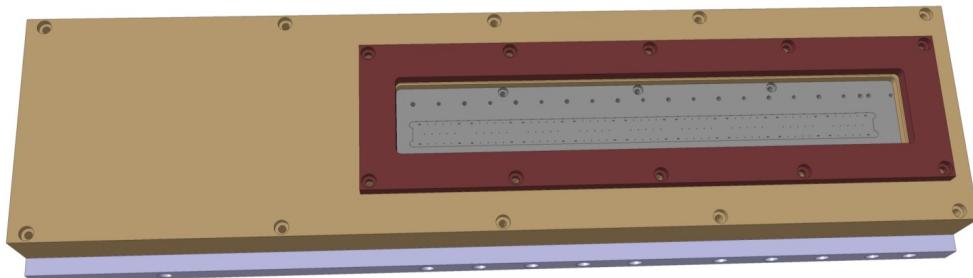


New version of HIC assembly table



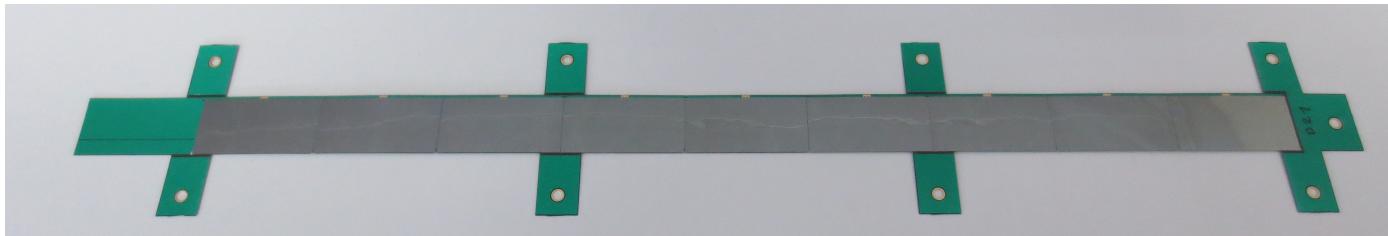
Metrology verification

Vacuum chuck planarity: $< 15 \mu\text{m}$



Chuck planarity (already good for the current version) will be further improved for final version:

- target: $\sim 5 \mu\text{m}$



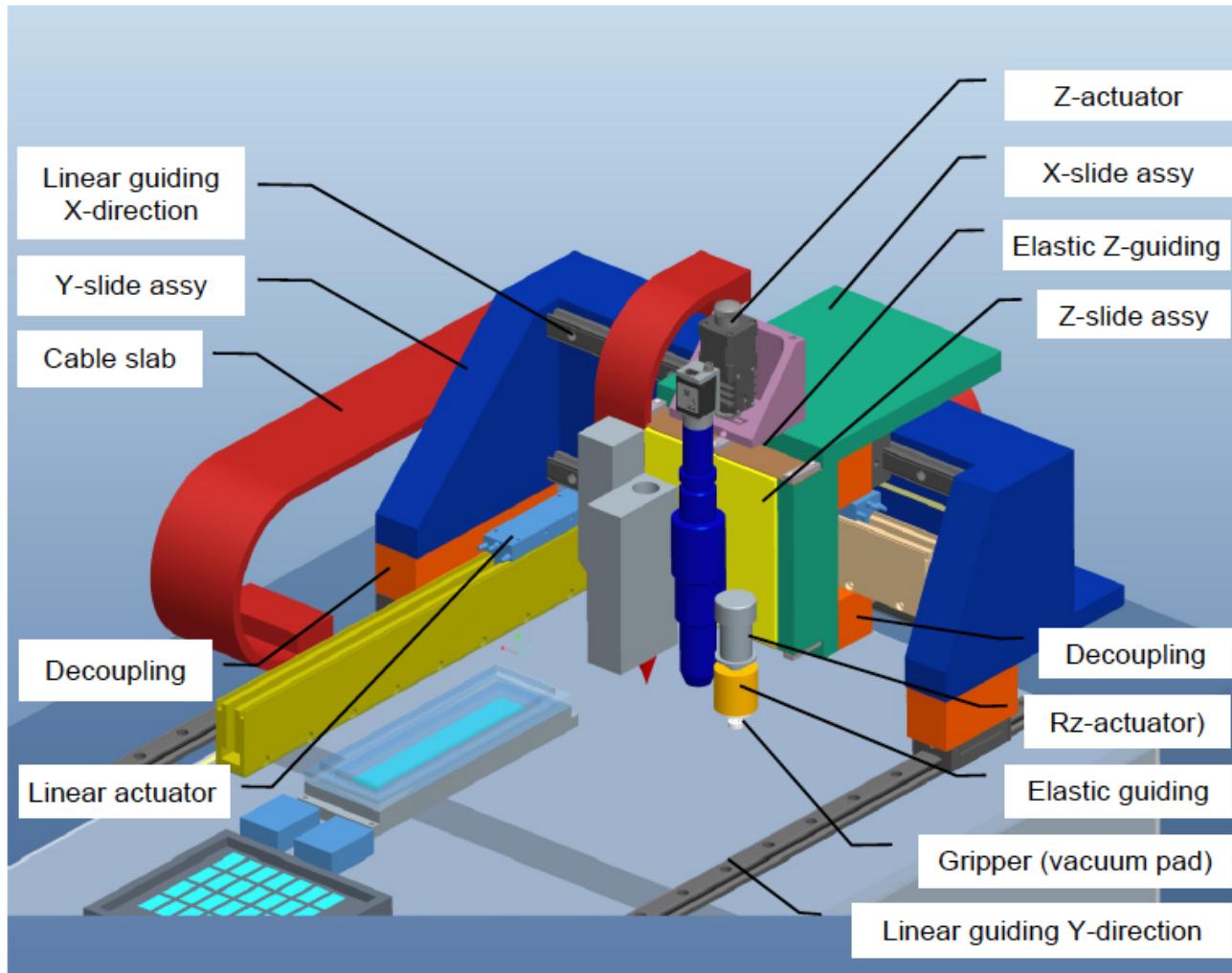
Module Assembly Machine

IB and OB module assembly

- Semi-automatic procedure
- custom machine (specialized company)

Status

- Contract adjudicated to IBS (NL)
- Delivery of first prototype October 15



6 Machines

Inner Barrel & MFT

- CERN

Outer Barrel

- Bari
- Strasbourg
- Liverpool
- Pusan
- Wuhan

Same machines used also for chip testing

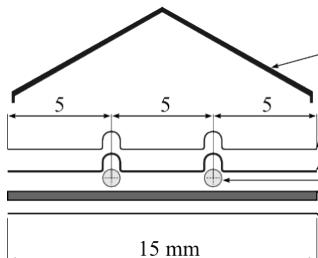
- CERN
- Pusan

Independent machine for chip testing

- Yonsei (Seoul)

Inner Barrel Stave - thermal test

Transversal section:



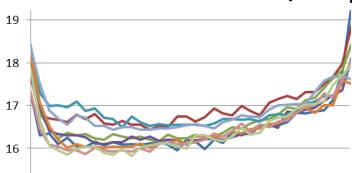
$P_{in} = 1 \text{ bar}$
 $T_{in} = 15.8^\circ \text{C}$
 $Q = 3 \text{ L/h}$
 $T_{out} = 16.6^\circ \text{C}$
 $P_{out} = 0.7 \text{ bar}$



Heating is provided by dummy metalized chip : thickness= 50 μm chip + 20/200 nm Titanium /Platinum

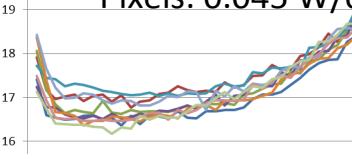
Nominal

Periphery: 0.145 W/chip
 Pixels: 0.03 W/chip



50% safety factor

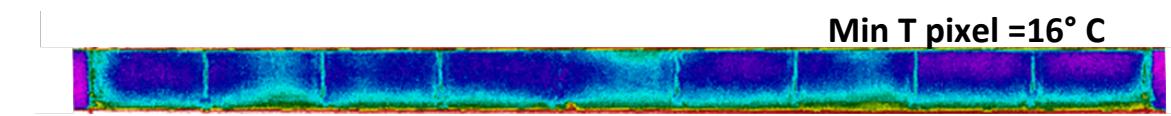
Periphery: 0.217 W/chip
 Pixels: 0.045 W/chip



status

verification of thermal behaviour with

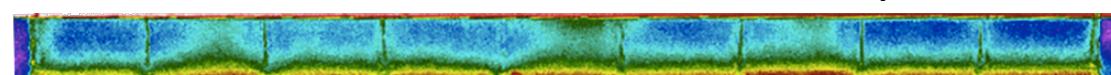
- non uniform power dissipation
- uniform layer of glue



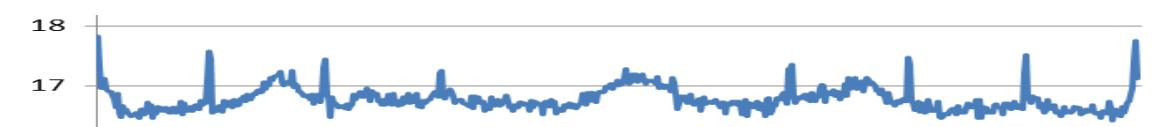
Max T periph=17.5°C



Min T pixel =16.5°C



Max T periph=18.5°C



ongoing

verification of thermal behaviour with

- non uniform power dissipation
- no glue at the periphery (2mm) of the chip

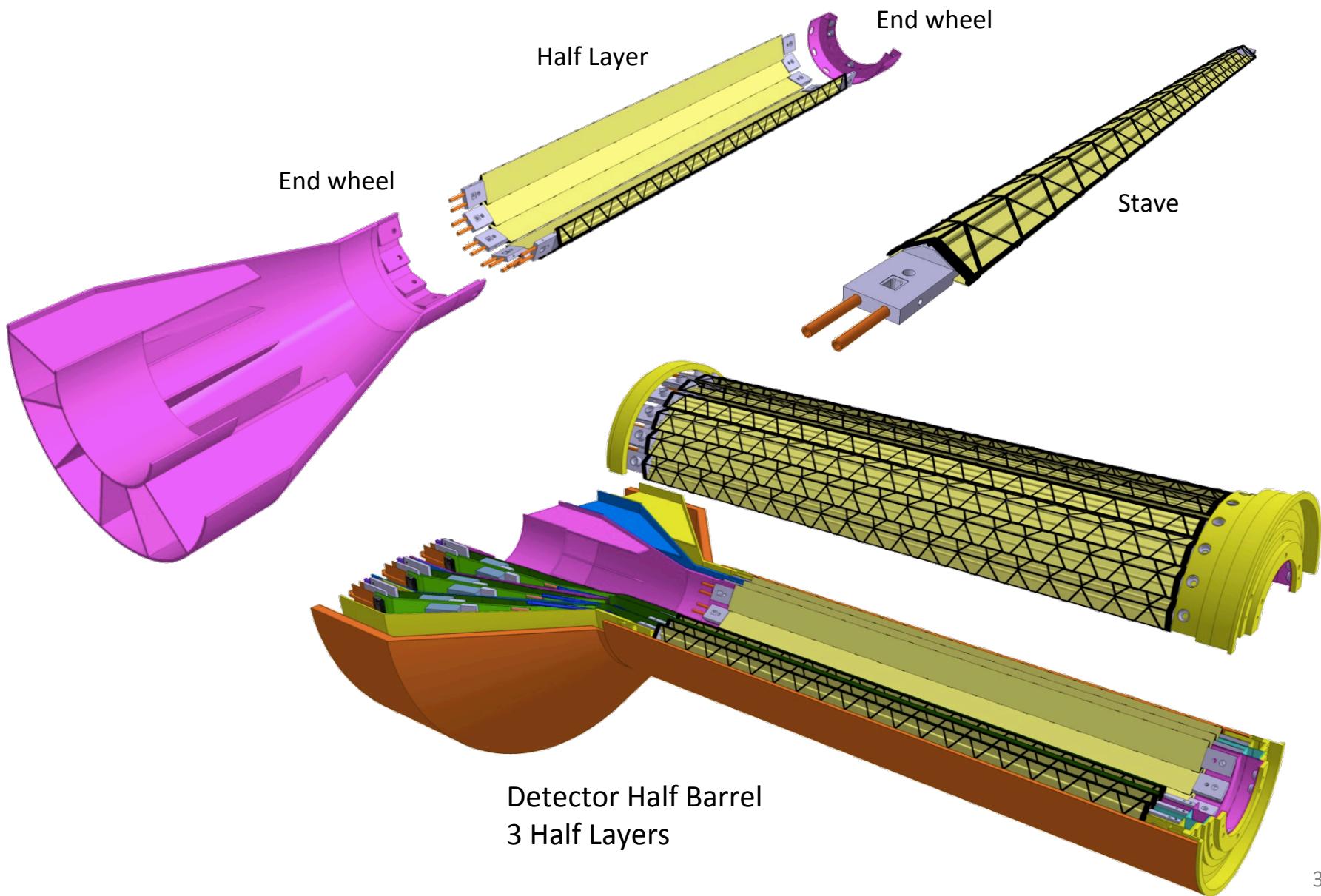
no glue



glue

no glue

Inner Barrel



Inner Barrel – full-scale prototype

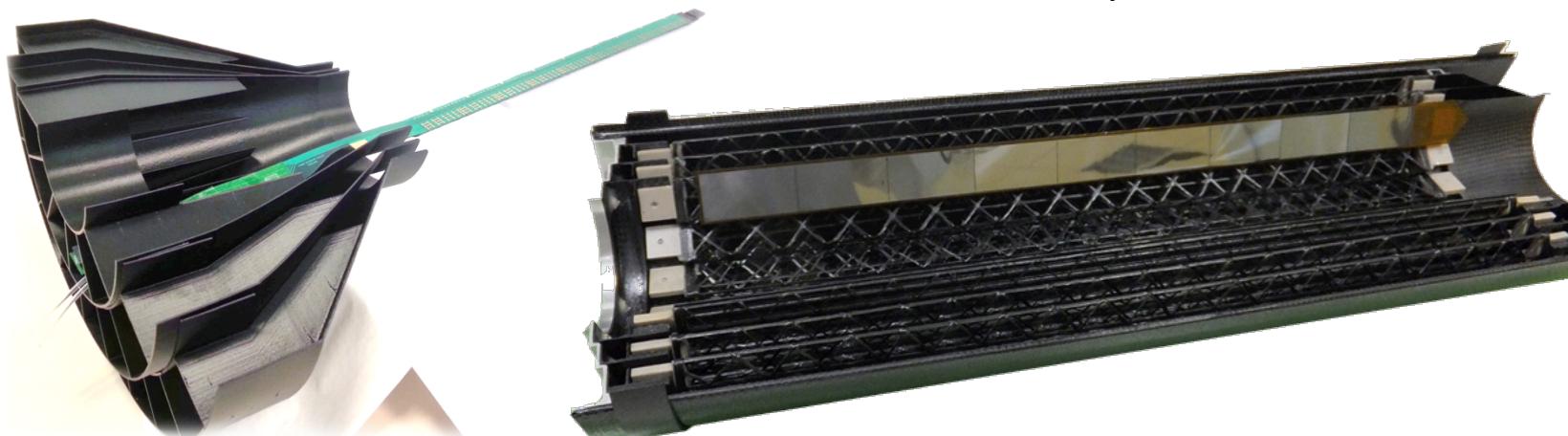
Structural Sandwich

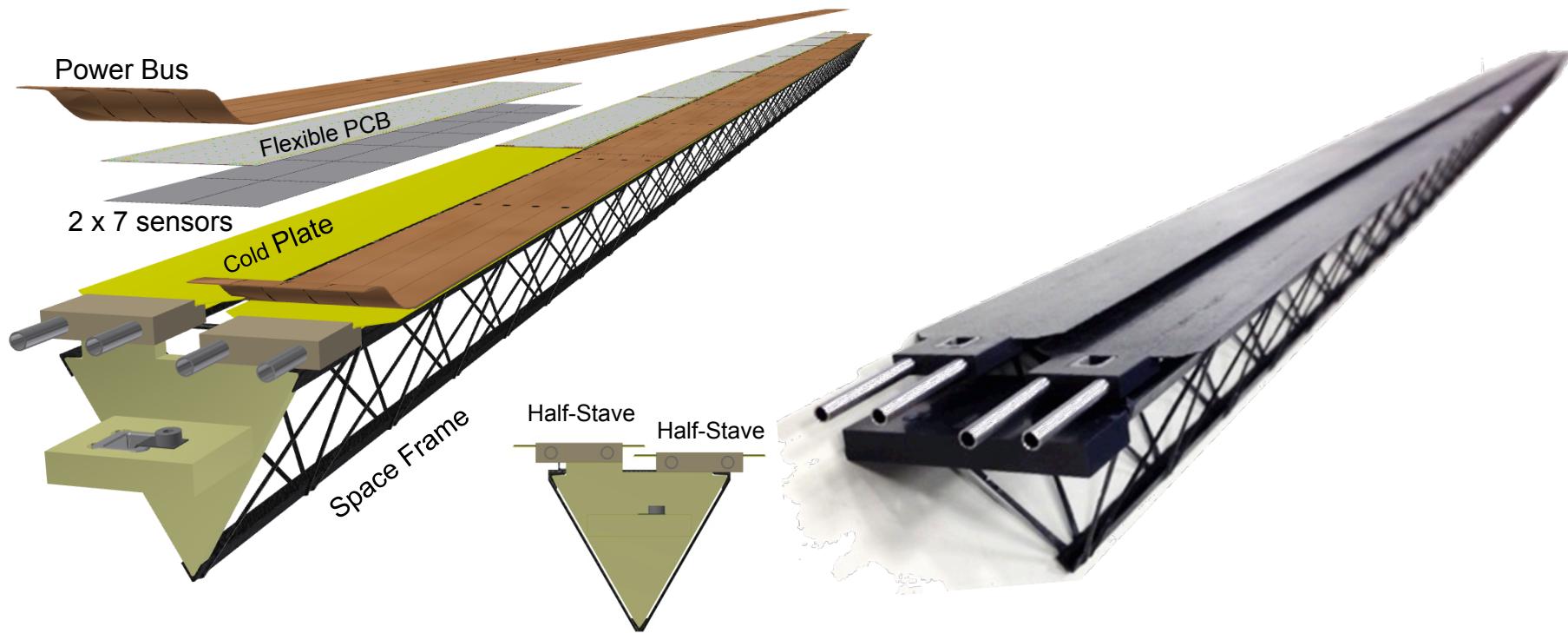


Prototype

Layer 1

Layer 2





Outer Barrel (OB)

<radius> (mm): 194, 247, 353, 405

Nr. staves: 24, 30, 42, 48

Nr. Chips/layer: 6048 (ML), 17740(OL)

Power density < 100 mW / cm²

Length (mm): 900 (ML), 1500 (OL)

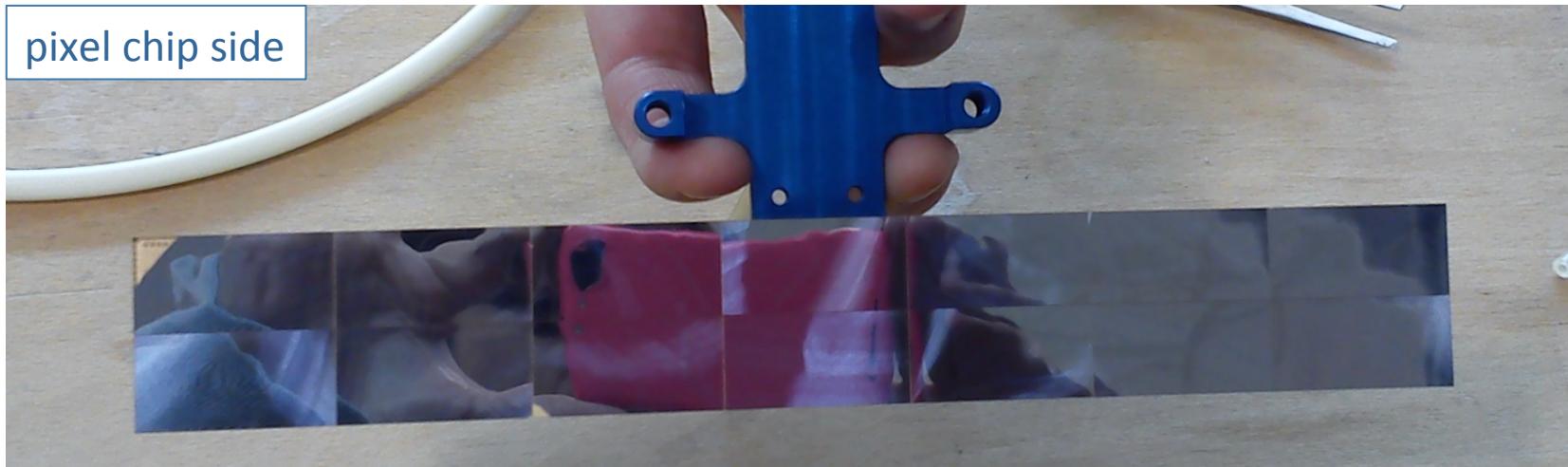
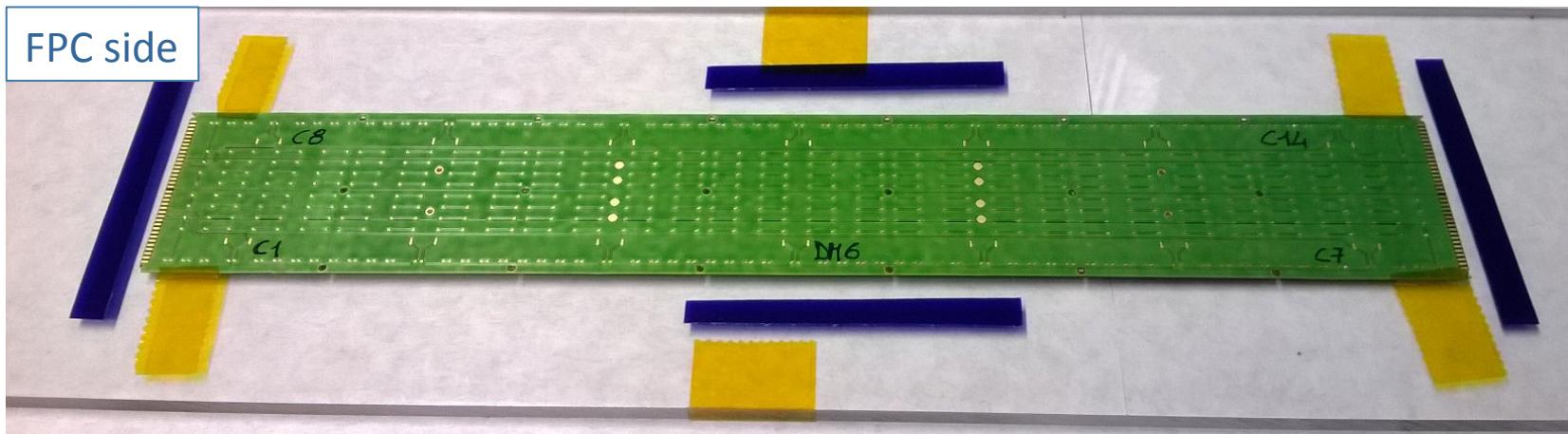
Nr. modules/stave: 4 (ML), 7 (OL)

Material thickness: ~ 1% X_0

Throughput (@100kHz): < 3Mb/s × cm⁻²

HIC: Interconnection of pixel chip on flexible printed circuit (FPC)

Bari

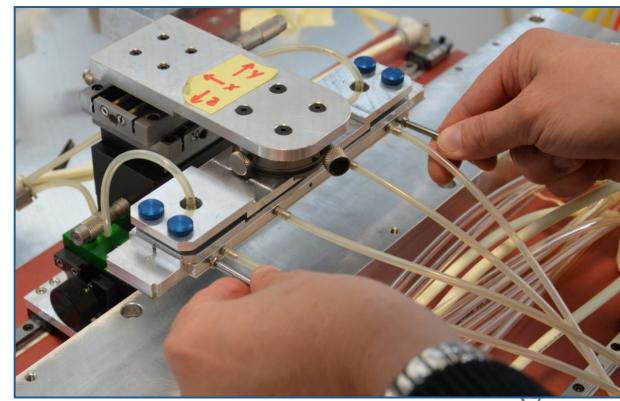
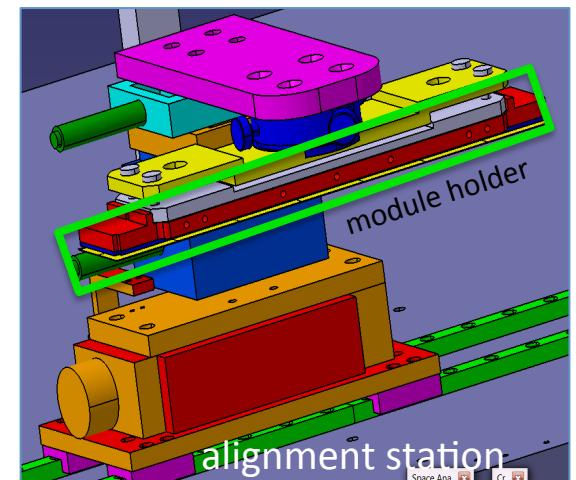
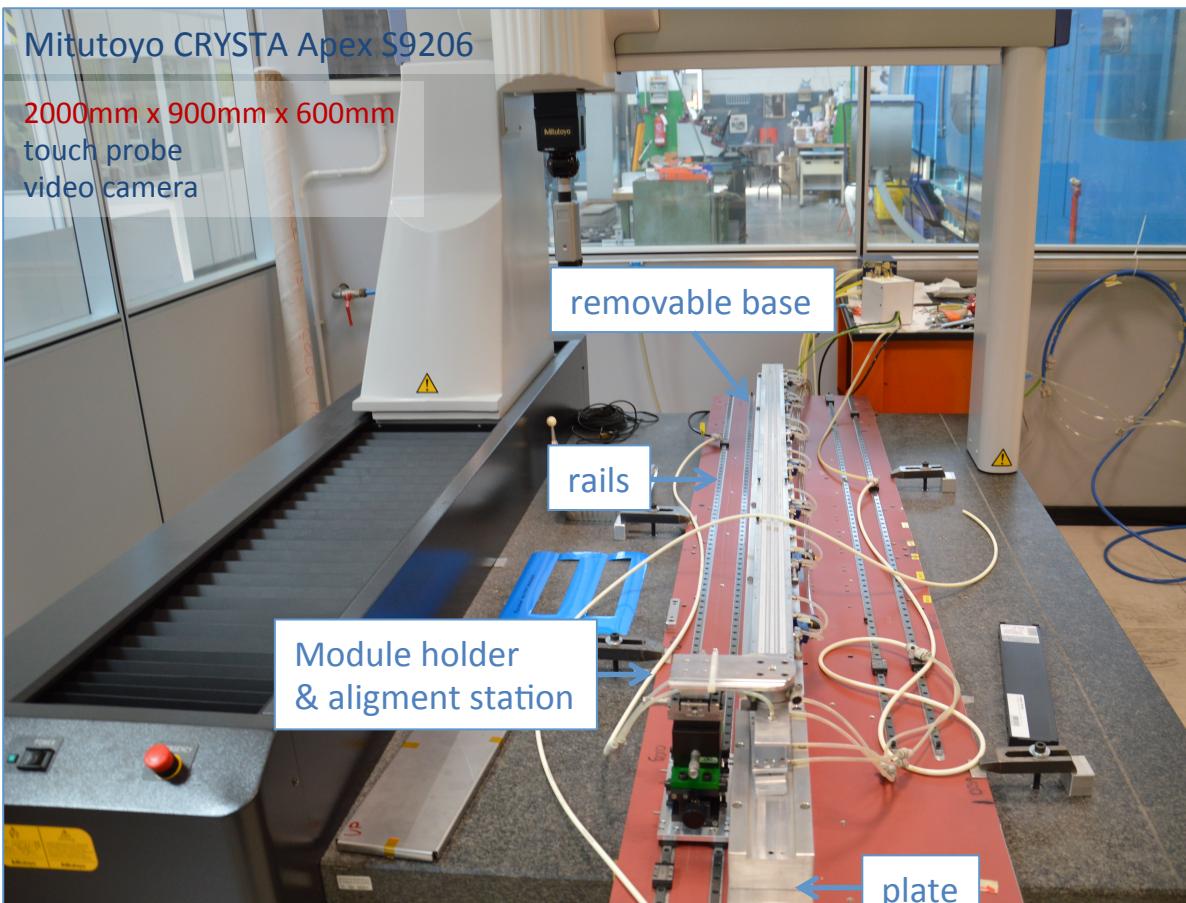


OB Half Stave – Assembly Jig

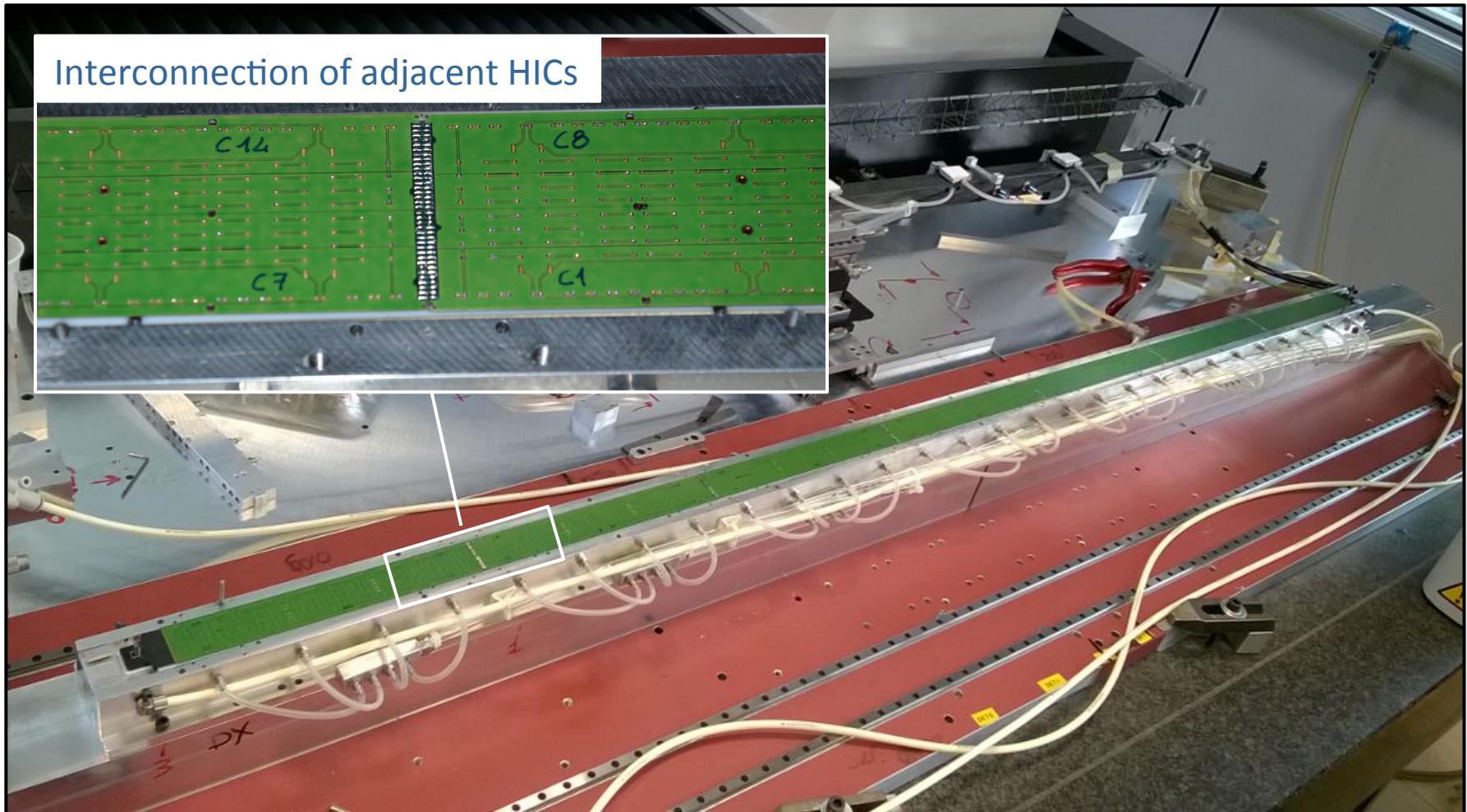
Main components

- Removable base (vacuum chuck that holds the cold plate)
- Rails to guide the longitudinal movement of the alignment station
- Alignment station
- Module holder

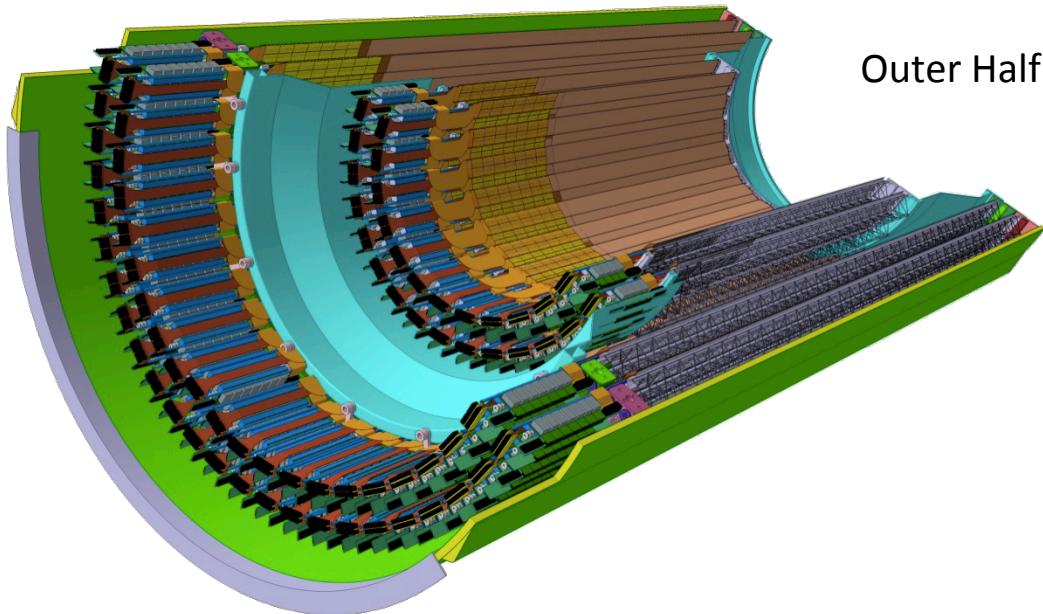
Turin



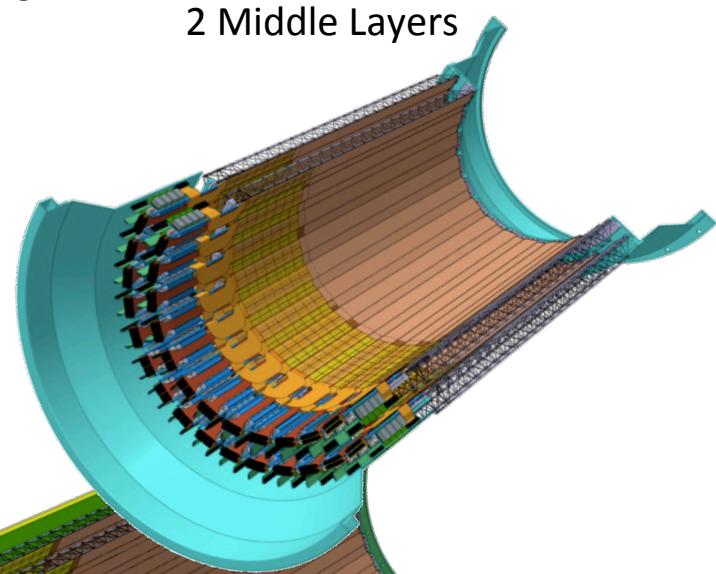
Half-stave equipped with dummy HICs (dummy silicon chips)



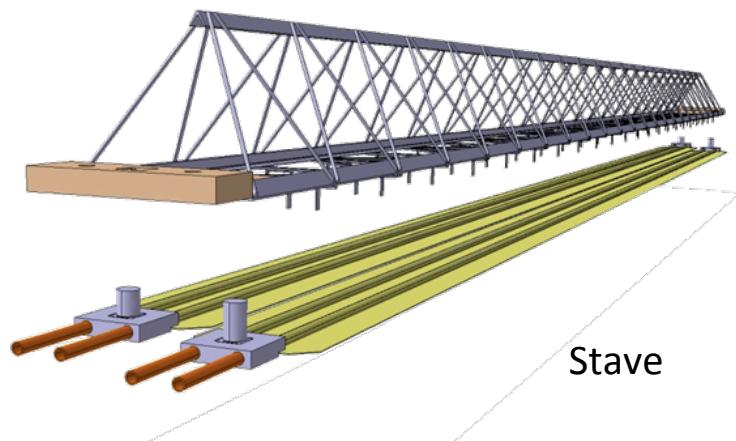
ITS Outer Detector Barrel



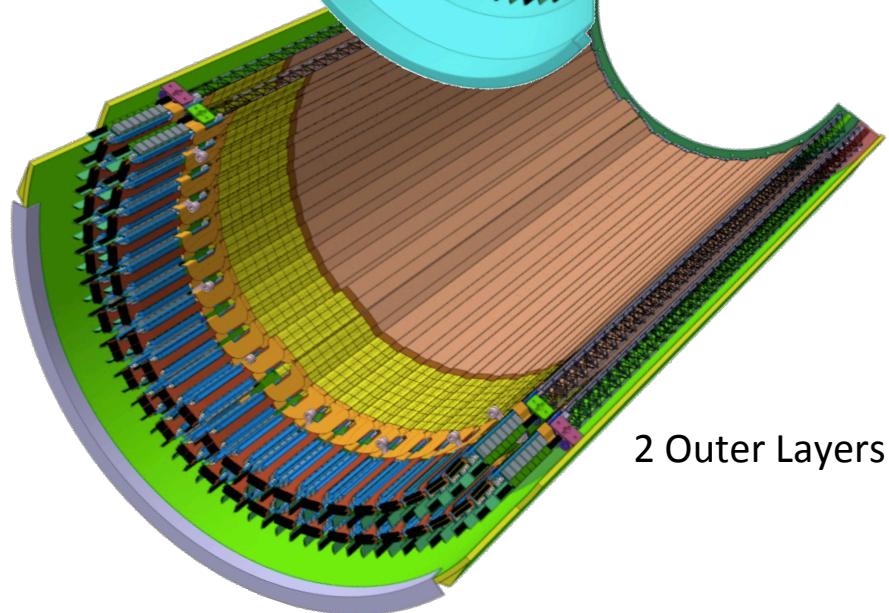
Outer Half Barrel



2 Middle Layers

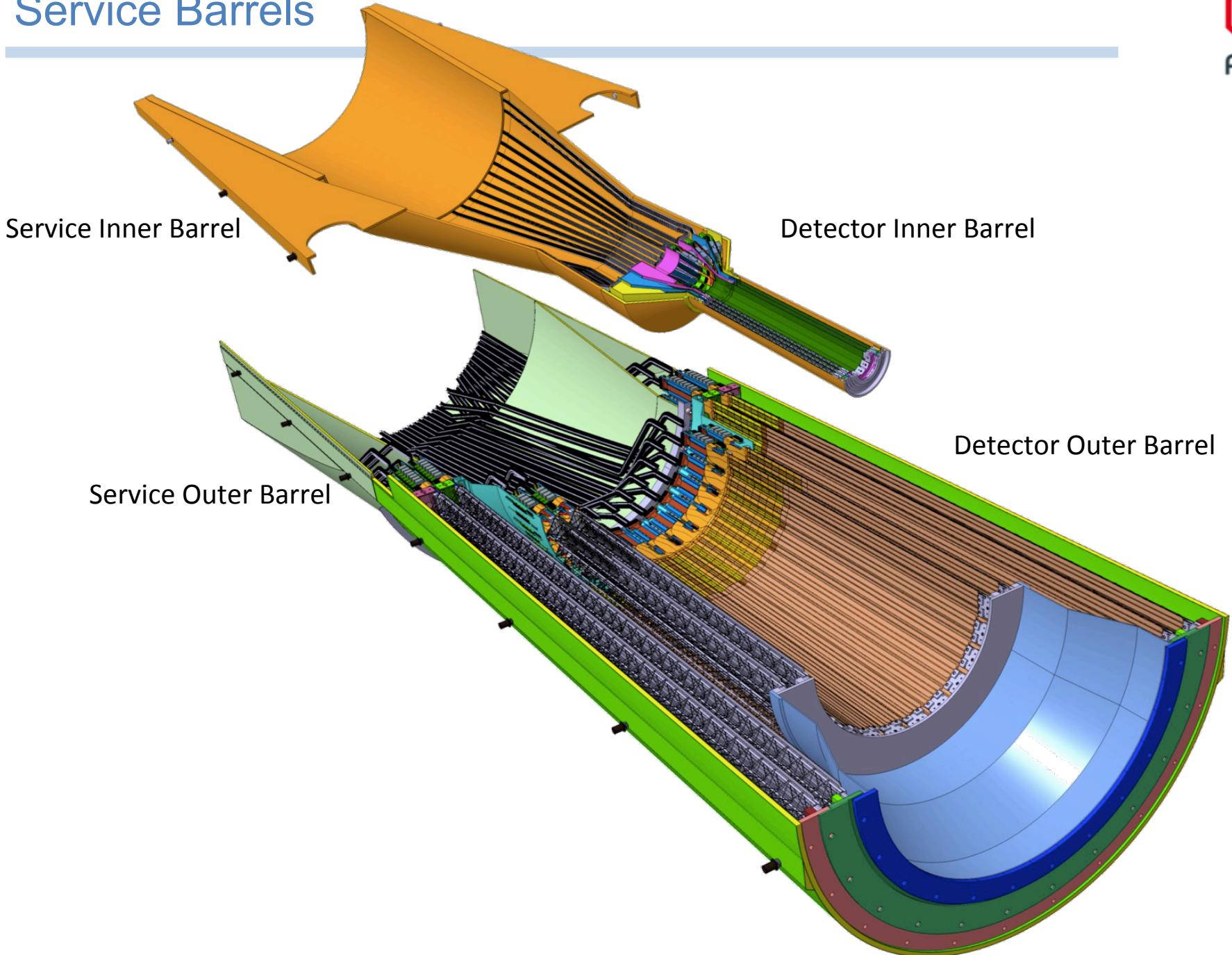


Stave



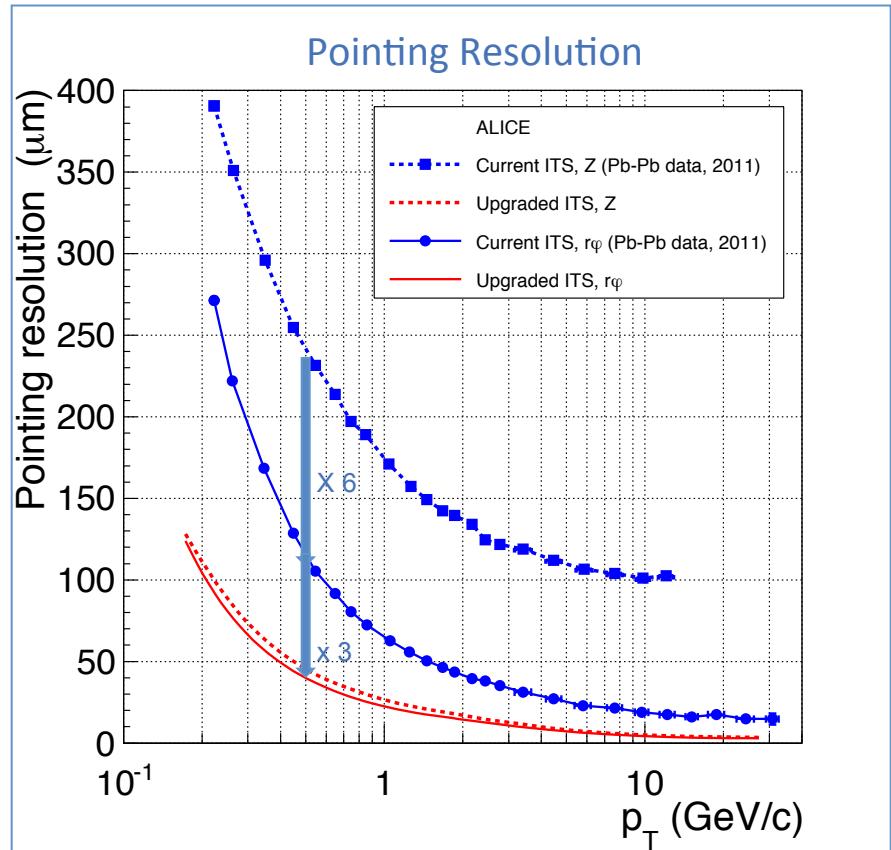
2 Outer Layers

Service Barrels

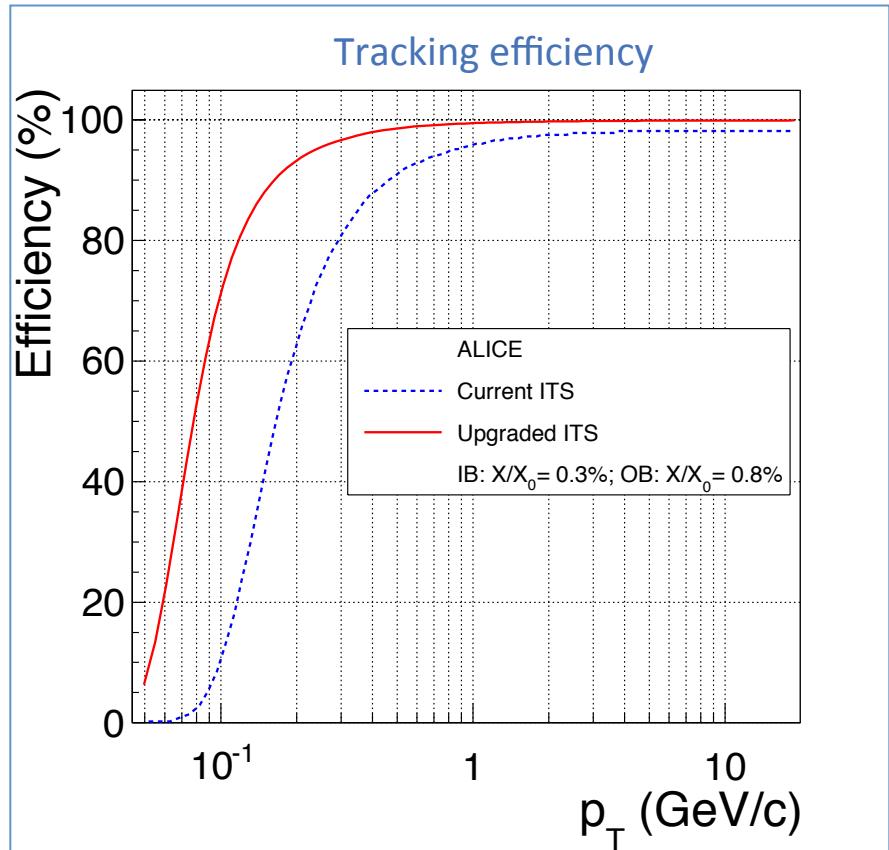


Performance of new ITS (MC simulations)

Impact parameter resolution



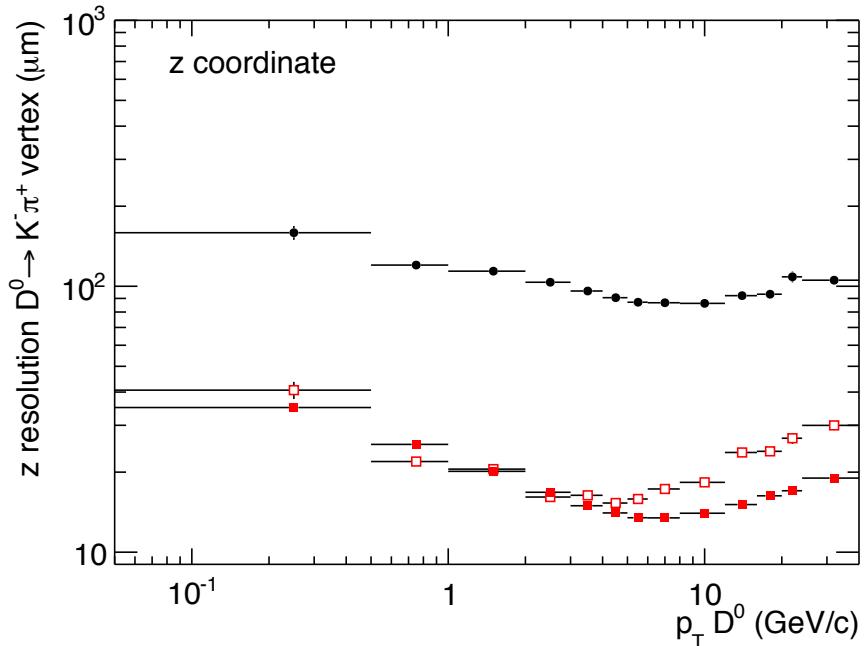
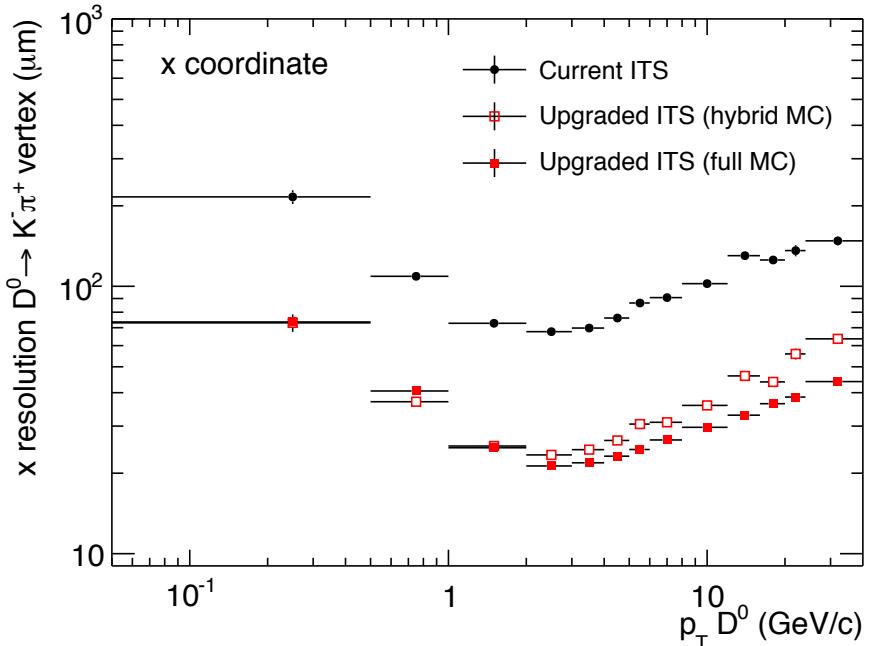
Tracking efficiency (ITS standalone)



$\sim 40 \mu\text{m}$ at $p_T = 500 \text{ MeV}/c$

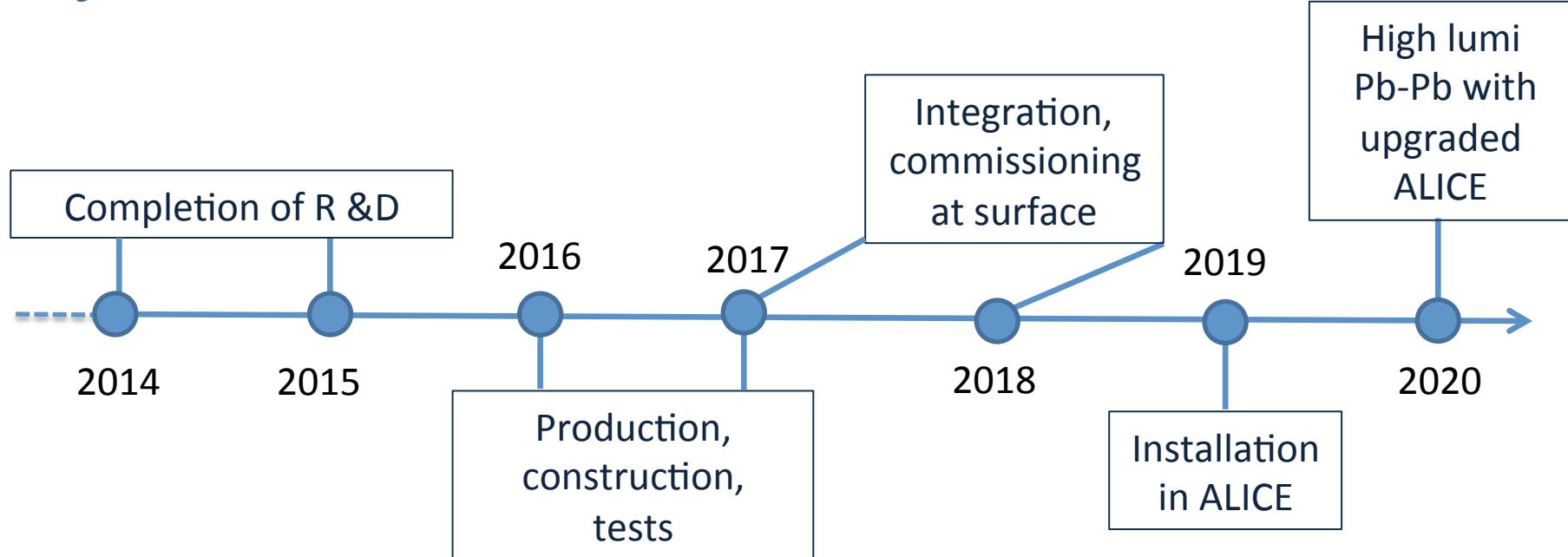
Performance of new ITS (MC simulation)

$D^0 \rightarrow K^-\pi^+$ secondary vertex position resolution



J. Phys. G (41) 087002

Project Timeline and Collaboration



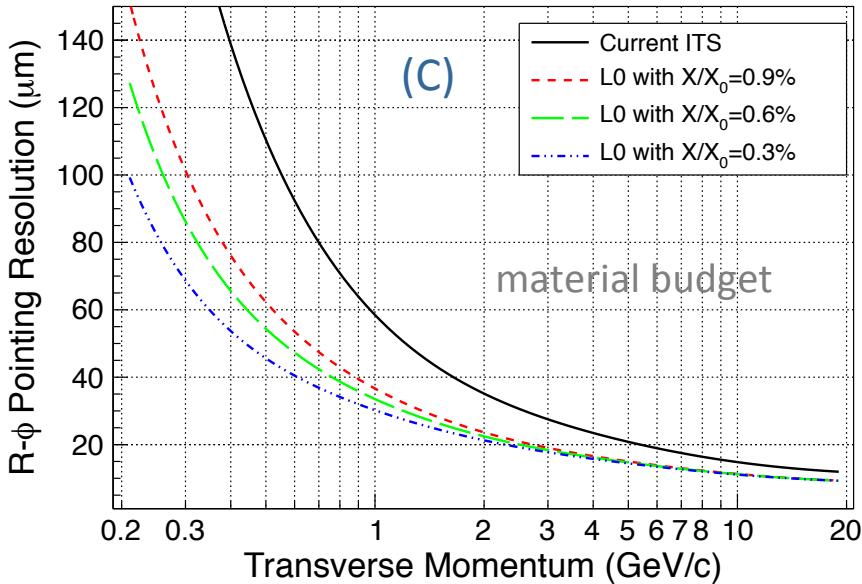
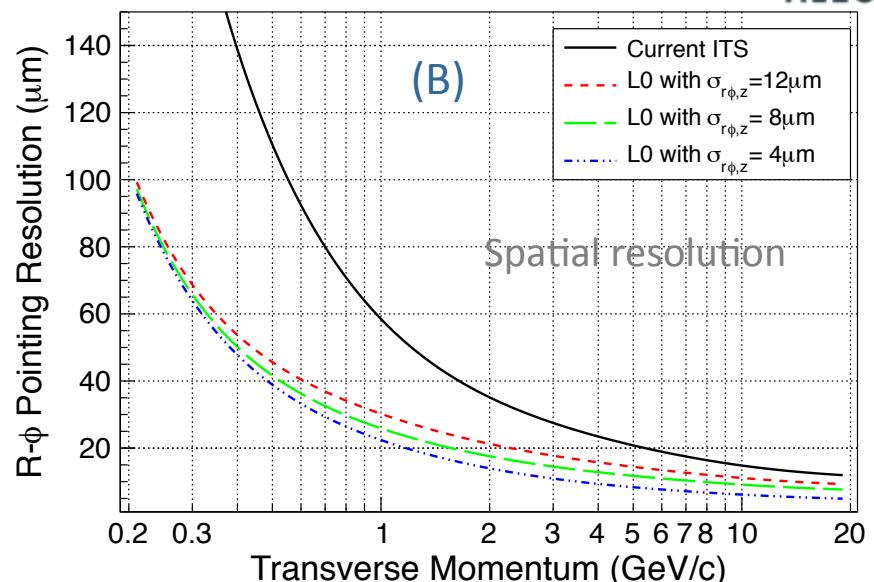
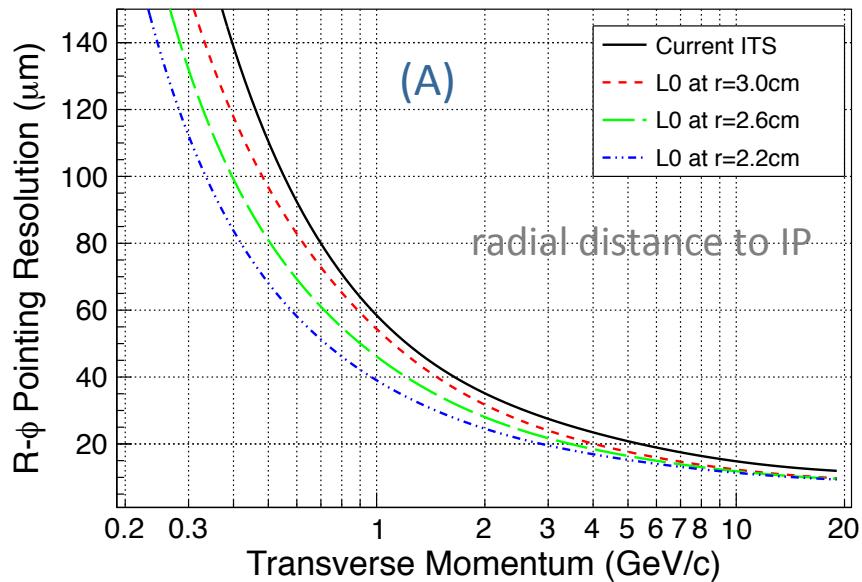
ALICE ITS Collaboration

[CERN](#), [China \(Wuhan\)](#), [Check Republic \(Prague\)](#), [France \(Grenoble, Strasbourg\)](#),
[Italy \(Aless., Bari, Cagliari, Catania, Frascati, Padova, Roma, Trieste, Torino\)](#),
[Indonesia \(LIPI\)](#), [Korea \(Pusan, Inha, Yonsei\)](#), [Netherlands \(Nikhef, Utrecht\)](#),
[Pakistan \(CIIT-Islamabad\)](#), [Russia \(St. Petersburg\)](#), [Slovakia \(Kosice\)](#),
[Thailand \(Suranaree, SLRI, TMEC\)](#), [UK \(Daresbury, Liverpool, RAL\)](#), [Ukraine \(Kharkov\)](#),
[USA \(Austin, Berkeley\)](#)

Institute = participated in current ITS

SPARES

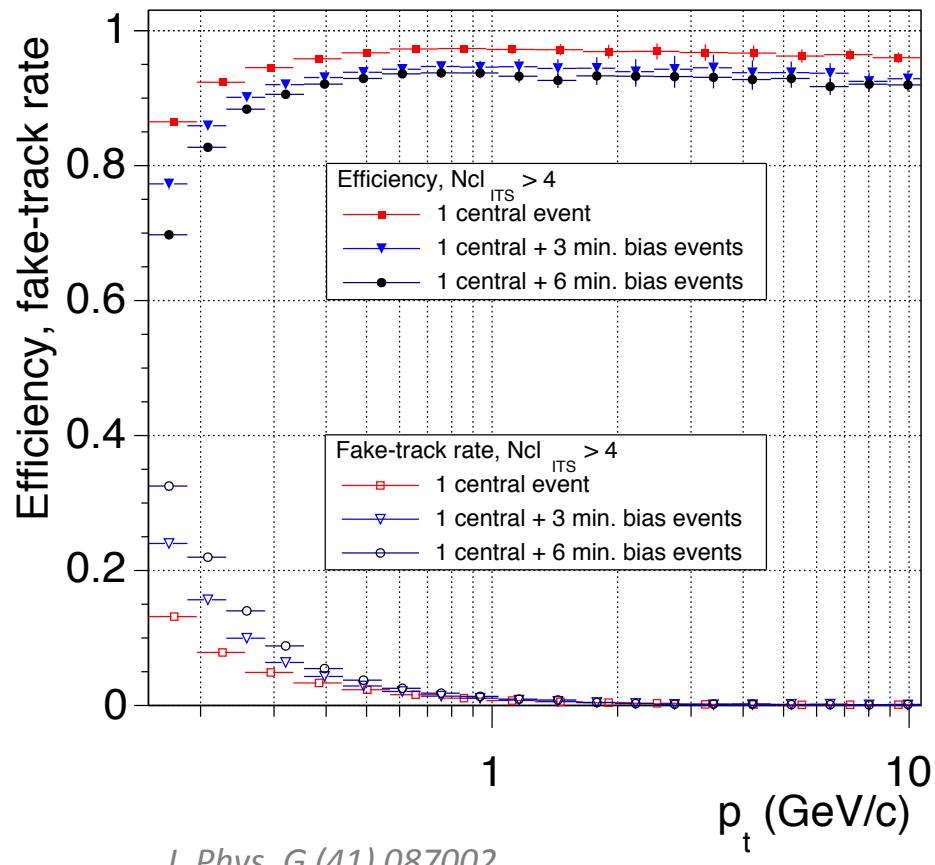
Impact parameter studies (ALICE ITS Upgrade)



- Current ALICE ITS
 - ◊ radial position of first layer: 39mm
 - ◊ x/X_0 : 1.14% per layer
 - ◊ spatial resolution (r-phi): 12 μm
- A) current ITS + L0: $x/X_0 = 0.3\%$, res.=4 μm ;
- B) current ITS + L0: $r = 22\text{mm}$, $x/X_0 = 0.3\%$;
- C) current ITS + L0: $r = 22\text{mm}$, $x/X_0 = 0.3\%$;

Performance of new ITS (MC simulations)

Matching efficiency between the tracks reconstructed in the upgraded ITS and TPC
for different values of event pile-up



The average event pile-up depends
on the interaction rate and detector
integration time

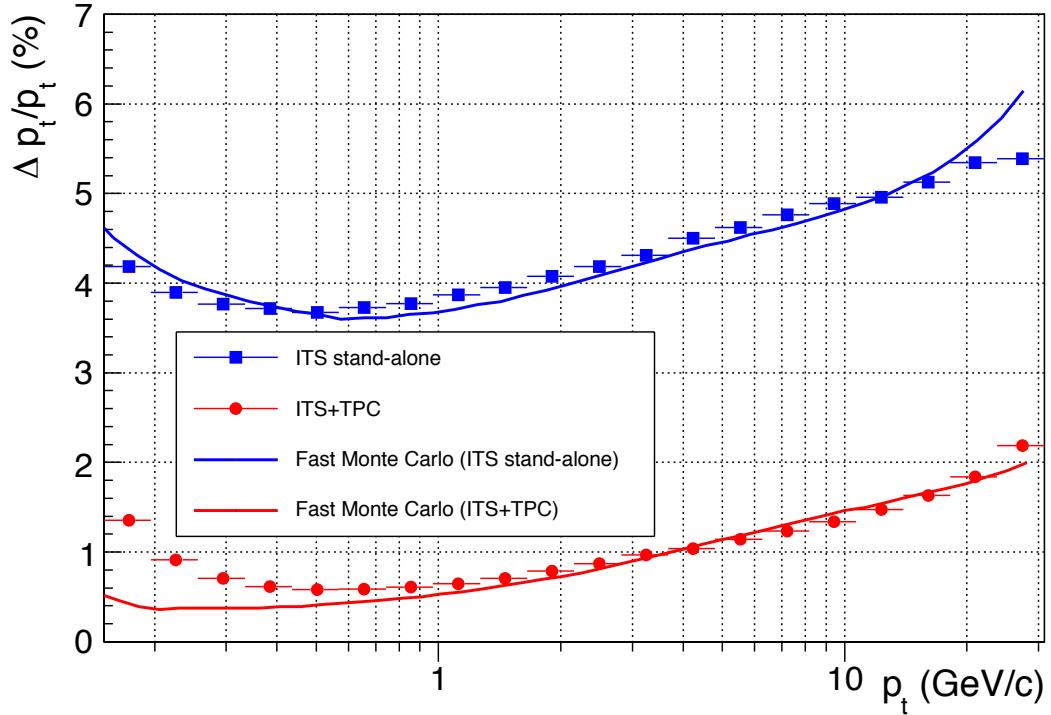
interaction rate 50 kHz
integration time: 4 – 30 μ s

For 30 μ s integration time (worst
case design):

$\langle \text{pile-up} \rangle = 1 \text{ central} + 1.5 \text{ min. bias}$

Performance of new ITS (MC simulations)

MOMENTUM RESOLUTION

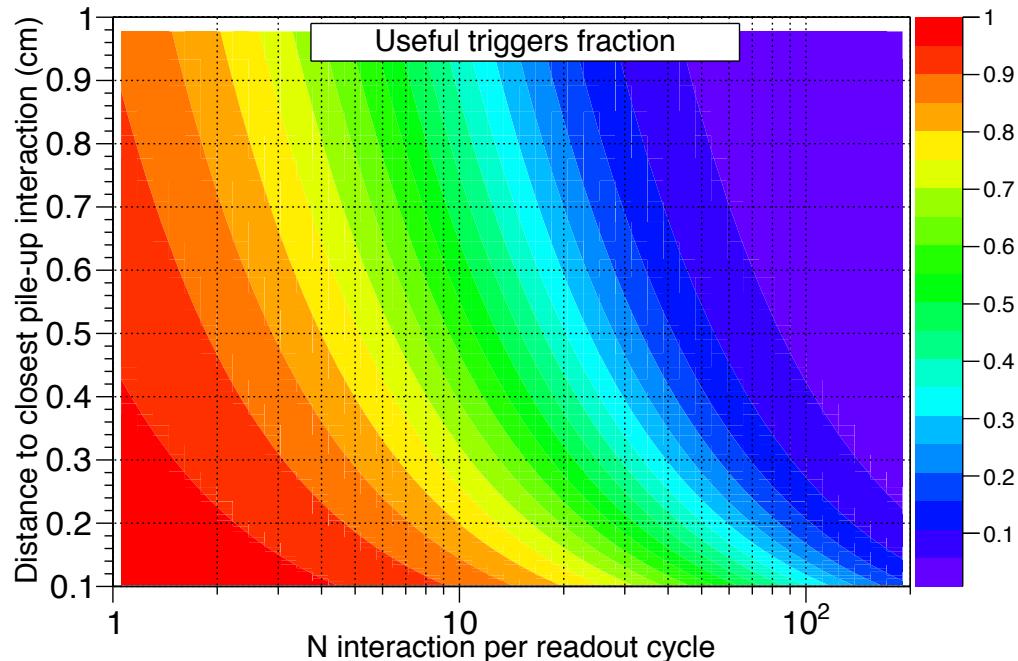
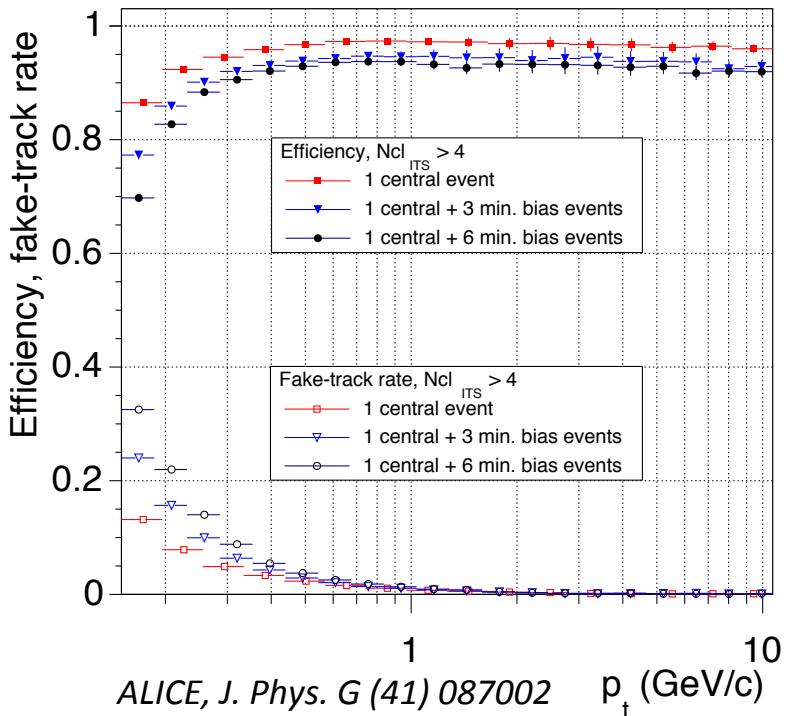


J. Phys. G (41) 087002

Transverse momentum resolution as function of p_T for primary charged pions for the upgraded ITS and current ITS. The results are shown for ITS standalone and ITS-TPC combined tracking.

How integration time and pile-up affect performance

ALICE ITS Upgrade



At 50 kHz Pb-Pb interaction rate

<pile-up> @ 20 μ s integration time: 1 central + 1 minimum bias

At 200 kHz pp interaction rate

<pile-up> @ 20 μ s integration time: 5 interaction

pALPIDE-3 - single pixel floorplan and layout

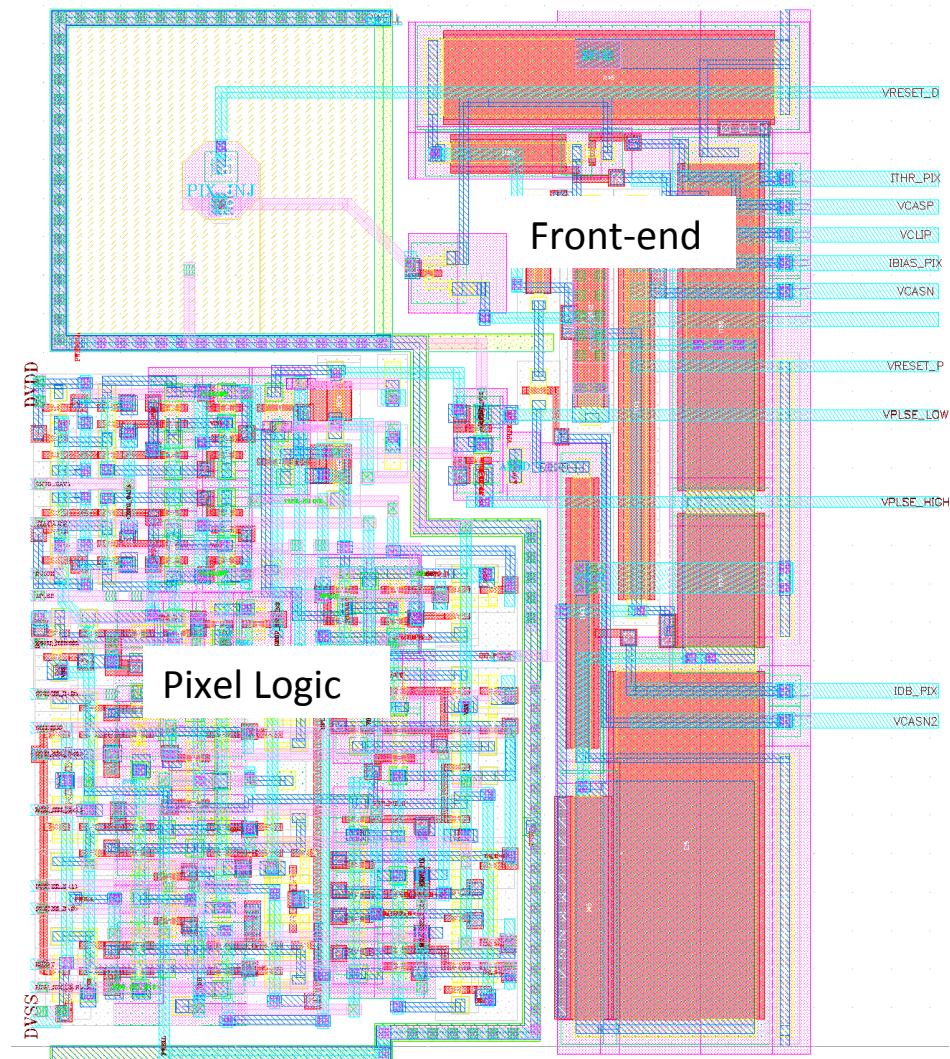
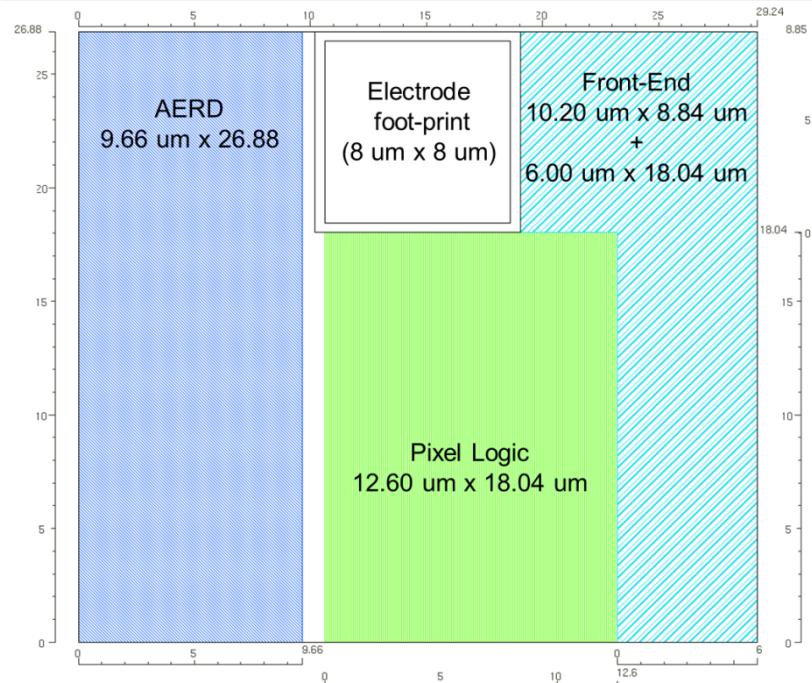
Final pixel size: $29.250 \mu\text{m} \times 26.880 \mu\text{m}$ (w × h)

Collection diode 8 μm

- 2 μm nwell width
- nwell-pwell spacing 3 μm

W 29.24 μm
H 26.88 μm

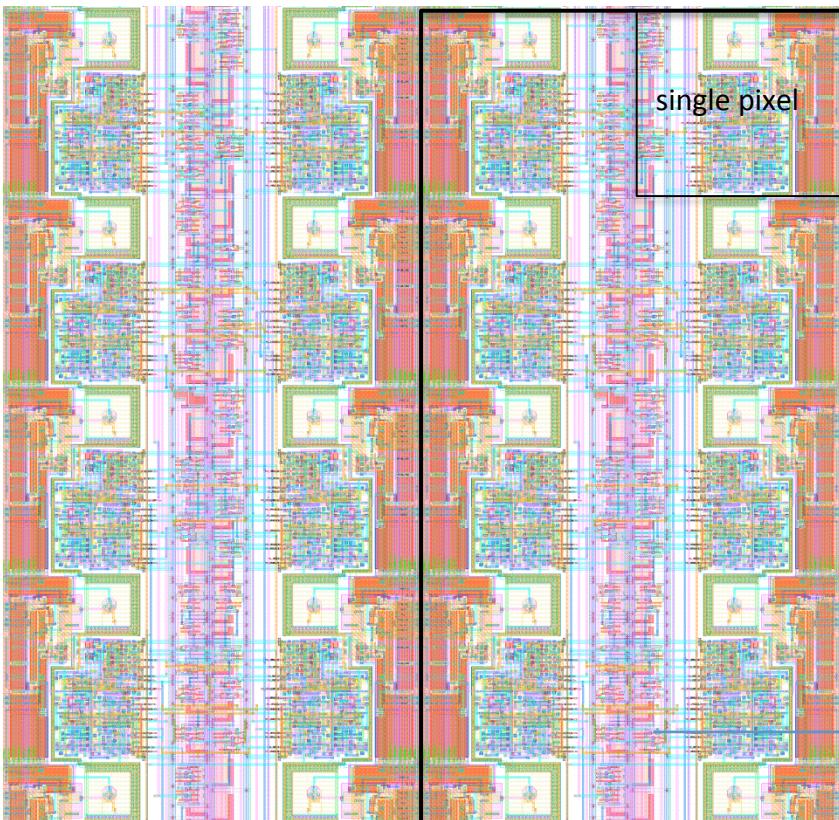
150 transistors



pALPIDE-3 – matrix layout

Pixel matrix (1024×512) size: 29.952 mm × 13.763 mm

4 x 5 pixels

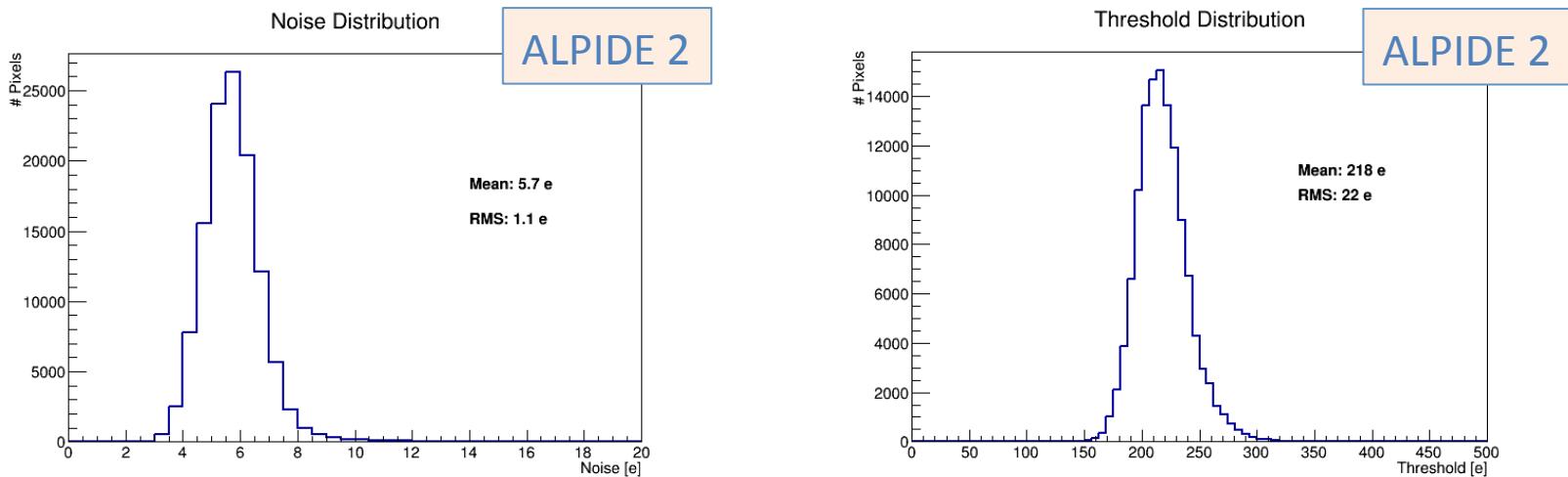


Priority Encoder implemented
with standard cells

8 sectors
128 columns/sector
width 3.74 mm/sector

Pixel double column

pALPIDE-3 - many improvements



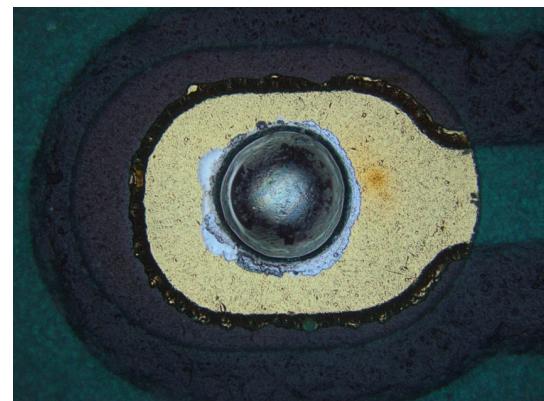
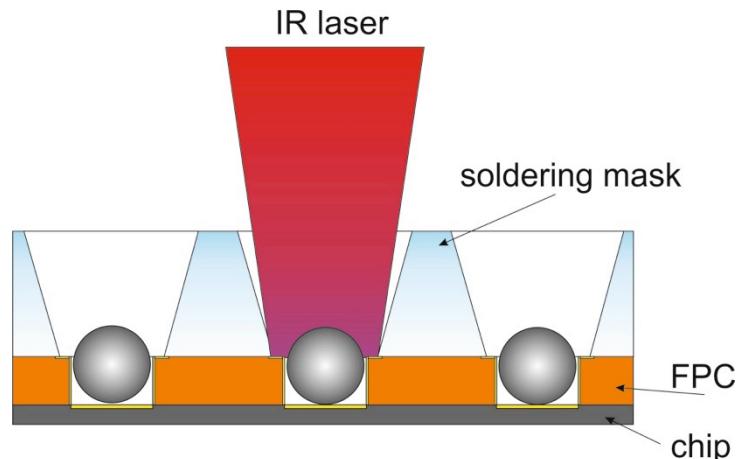
Main improvements

- Front End revision and optimization
 - Reduction of charge threshold spread and time response
- In-pixel 3-stage multi-event storage (1 in ALPIDE-1 & -2)
- Final version of digital periphery and I/O interface
- High-speed Output Link (1.2 Gbit/sec)
- ☞ Matrix divided in 8 sectors each with a different pixel

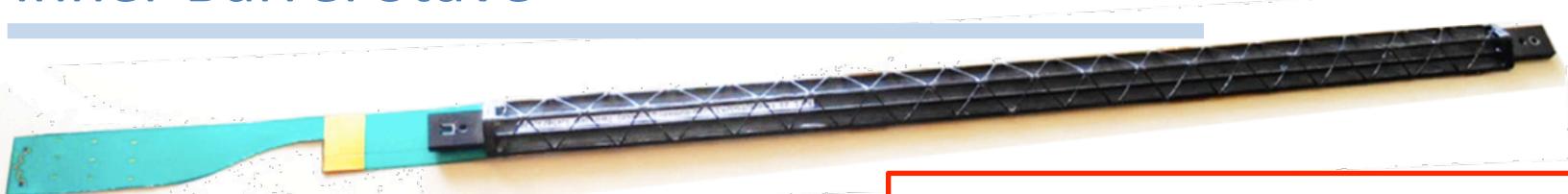
Interconnection of pixel chip to flex PCB

Laser Soldering

- Flux-less soldering of 200 µm diameter Sn/Ag(96.5/3.5) balls (227 °C melting T) in vacuum ($\leq 10^{-1}$ mbar)
- IR diode laser, 976 nm, 25 W, 50 mm focal length, 250 µm beam spot size
- Laser power modulated by pyrometer, programmable T profile ensures precise limitation of heating
- Soldering mask (in Macor® or Rubalit ®) used to press FPC on chip and guide soldering balls inside FPC vias
- Solder provides electrical and mechanical connection → no glue

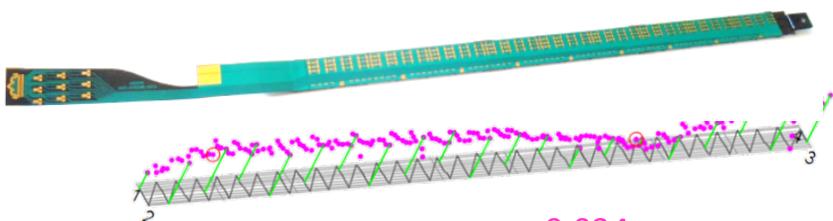


Inner Barrel Stave



Stave HIC+ Space frame assembly

Dimensional accuracy



+0.034 mm
- 0.034 mm

status

New master jig ([ready](#)) will improve stave accuracy

Space frame production

status

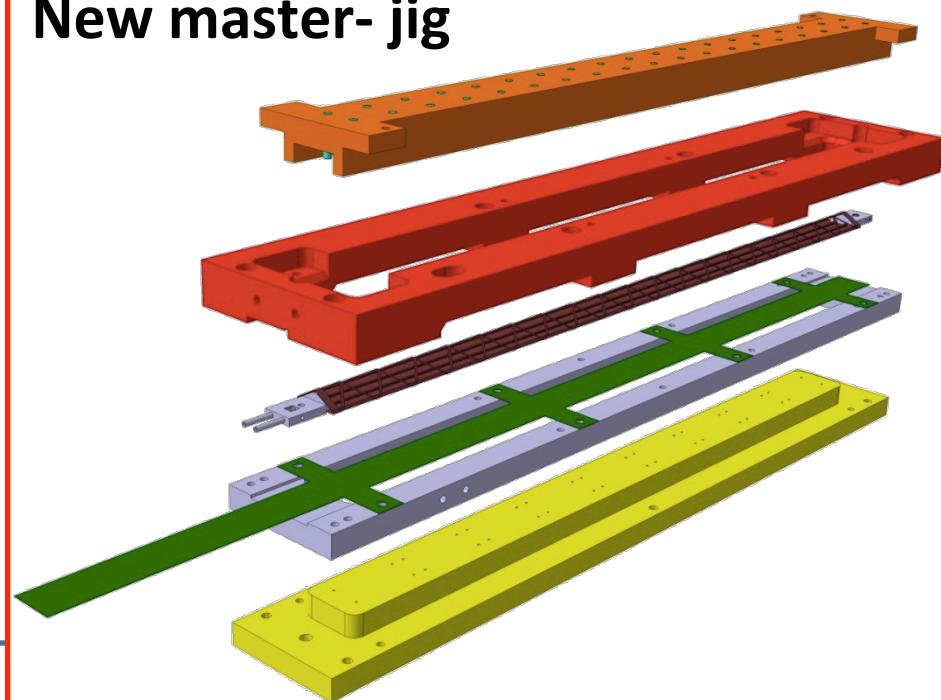
Available : n. 20 spaceframe

Ongoing

pre-production continues to prepare for final series production



New master- jig

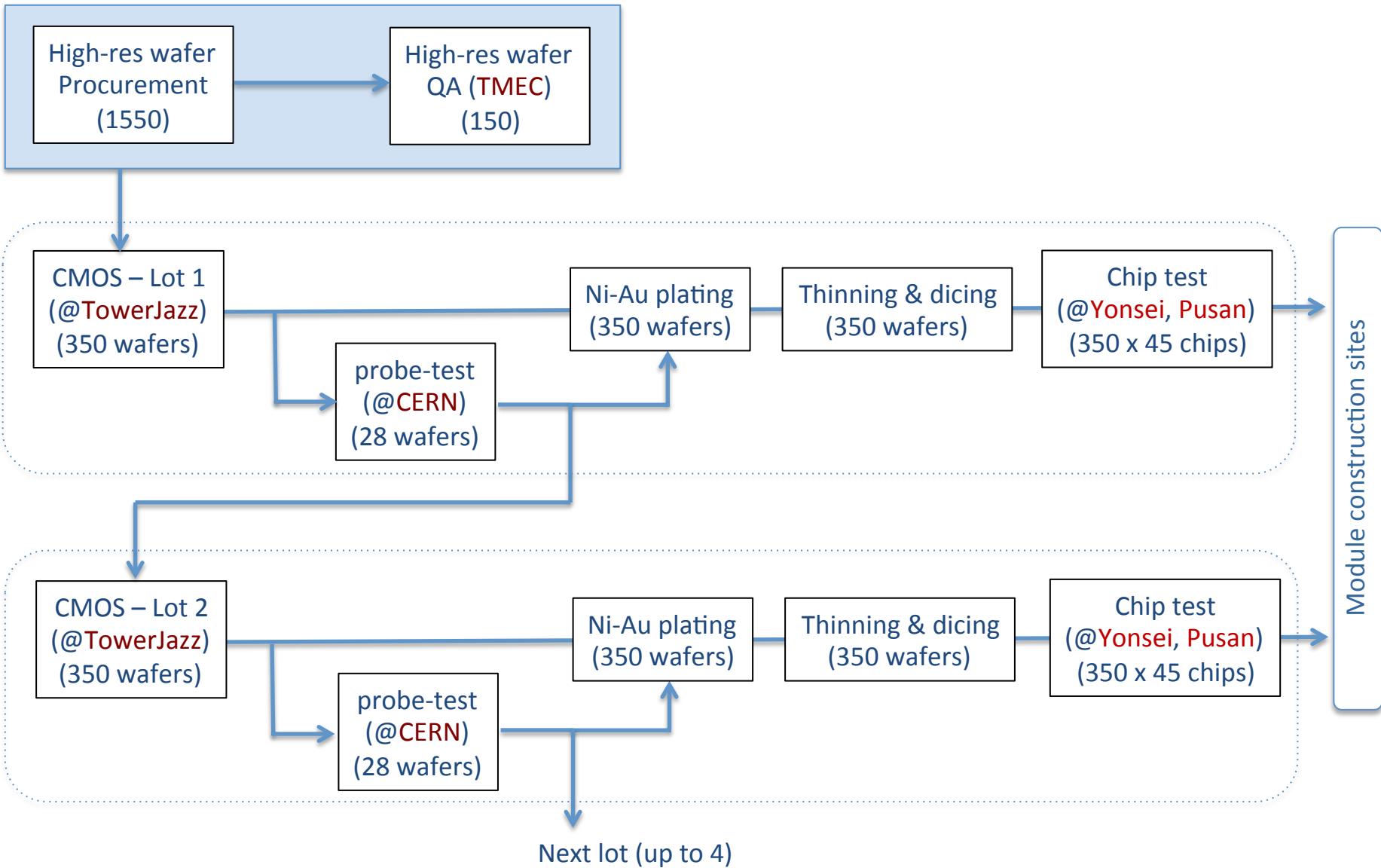


ongoing

New master jig produced and shipped from the Company,
arrival at CERN this week

Layout and curing process optimization: planarity achieved
 $\pm 0,028 \div 0,040$ mm

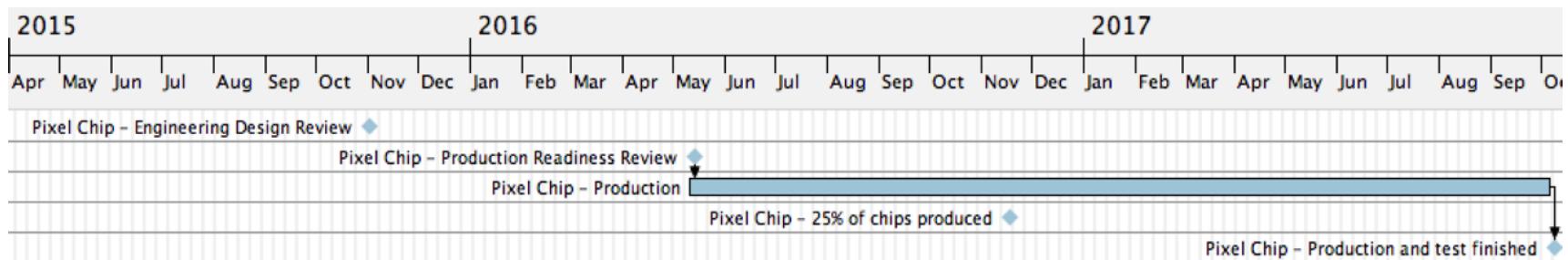
Pixel chip production flow chart



PIXEL Chip – Milestones

PIXEL Chip Development, Production and Test

1. Engineering Design Review (EDR) Oct 2015
2. Production Readiness Review (PRR) May 2016
3. Start Production May 2016
4. End Production Oct 2017

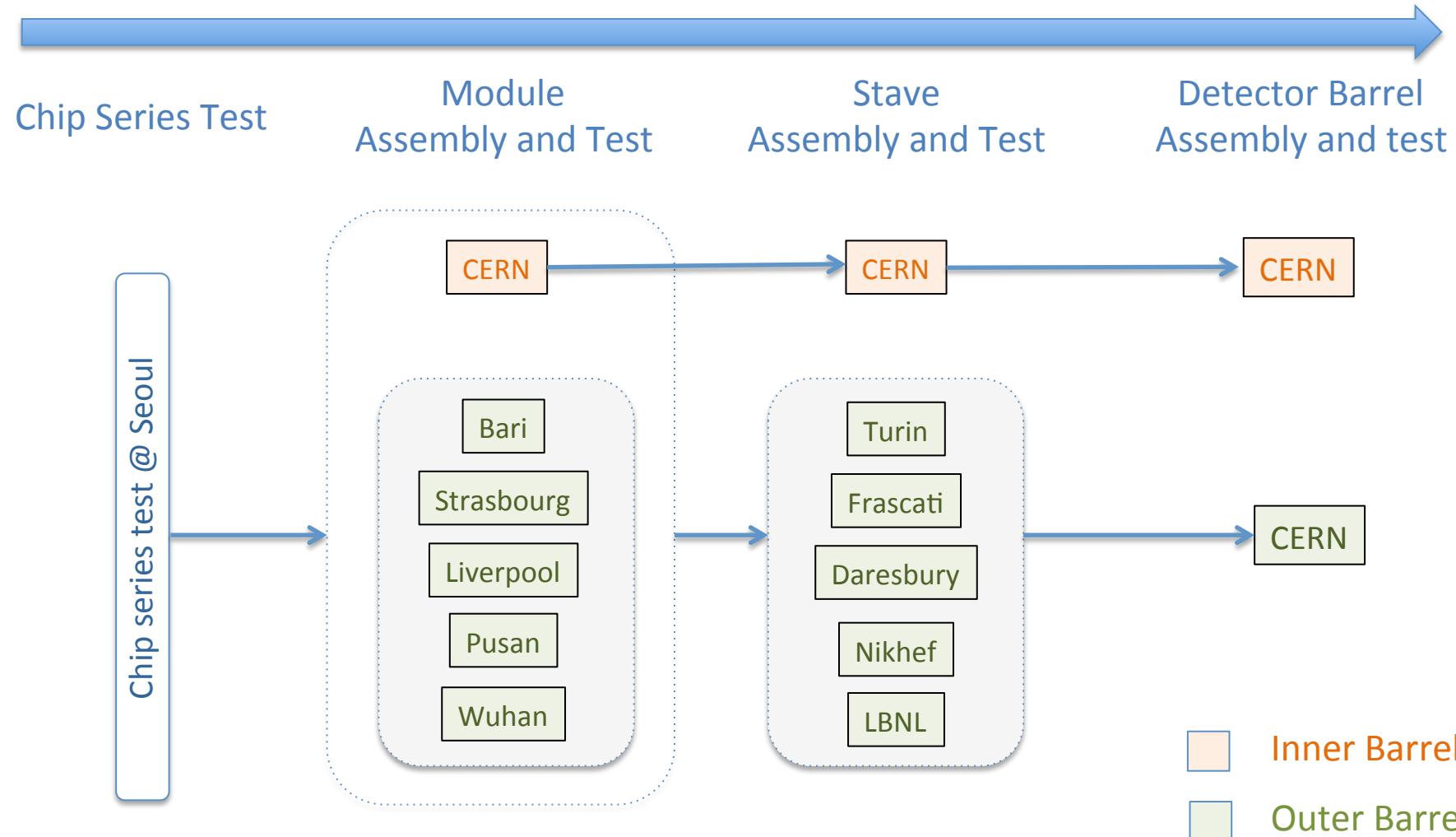


- ▶ Pixel chip production: Tower Jazz (Israel)
- ▶ Wafer probe testing (QA on 8% of wafers): CERN
- ▶ Ni/Au plating: Europe (tendering starting soon)
- ▶ Thinning & Dicing: Europe (tendering late summer)
- ▶ Chip Testing: Yonsei Uni (Seoul, South Korea), Pusan Uni (South Korea), CERN

█ baseline

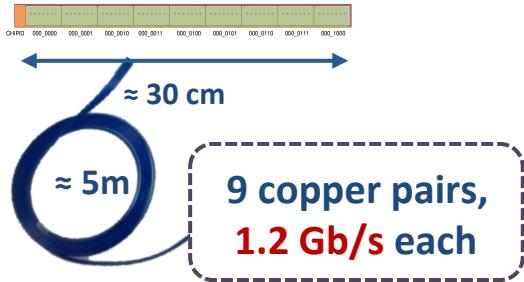
█ backup

Module and Stave production flow chart

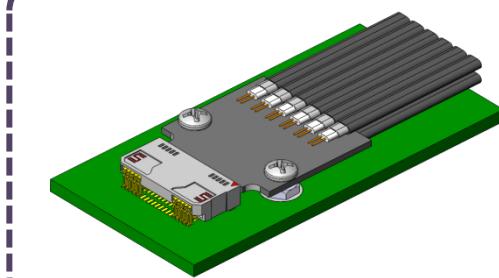


Readout Unit – system overview

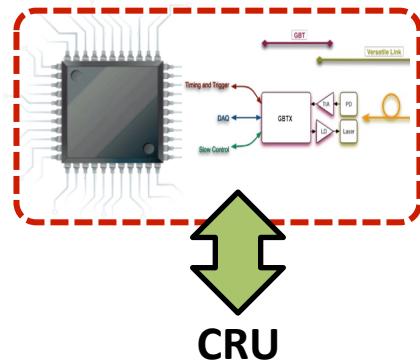
Inner layers (0, 1, 2) staves:
9 masters for each stave



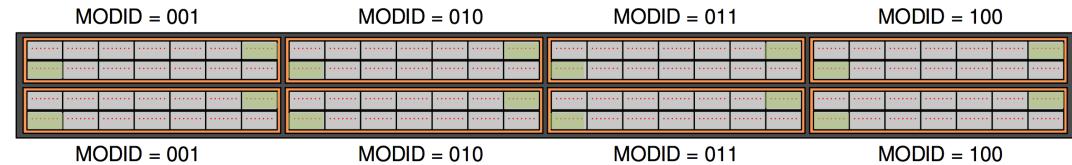
12 pairs Twinax copper assembly



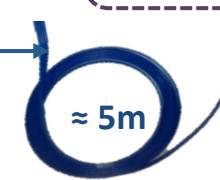
Readout Unit



Mid layers (3, 4) staves: 8 modules per stave, 2 master each



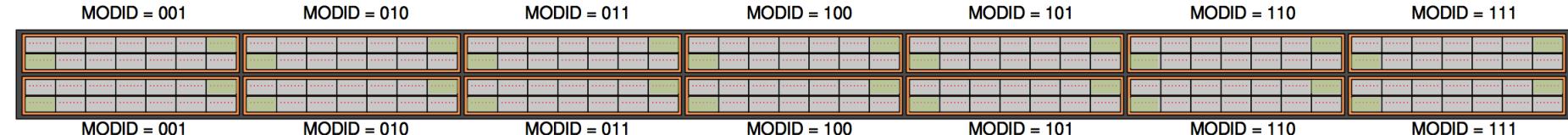
16 copper pairs,
400 Mb/s each



28 copper pairs,
400 Mb/s each



Outer layers (5, 6) staves: 14 modules per stave, 2 master each



Readout – single modular Readout Unit for all layers

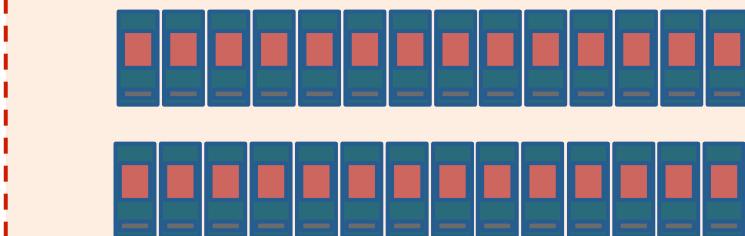


Inner Layers

Readout Unit

2 × 16 channel FPGA
per half stave (only
one used for inner
layers)

Power Unit

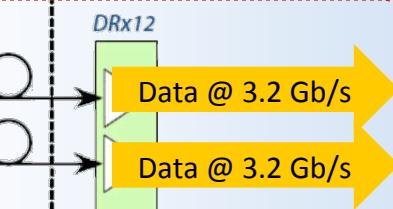
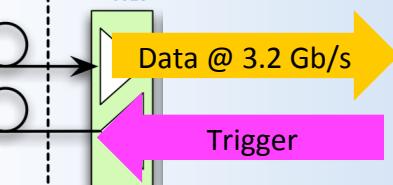
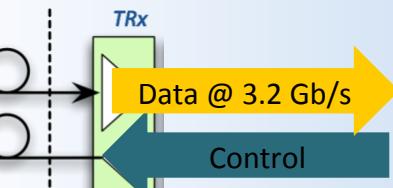
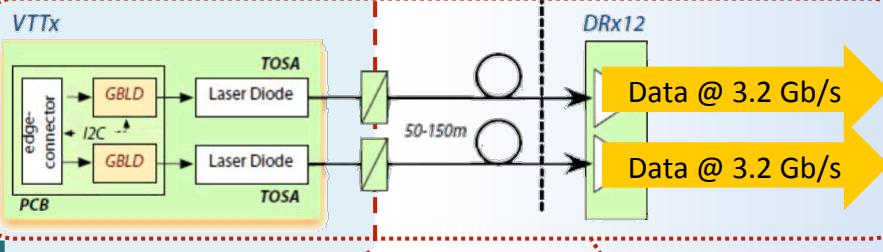
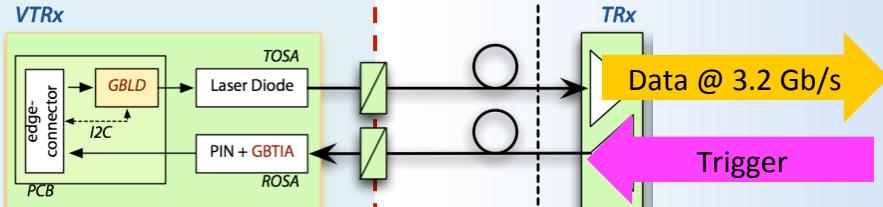
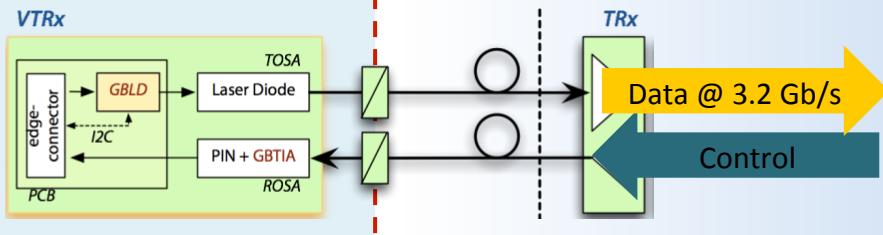


Control

Not mandatory for
“baseline” (Pb-Pb @ 50 kHz)
operations.

Independent to control system

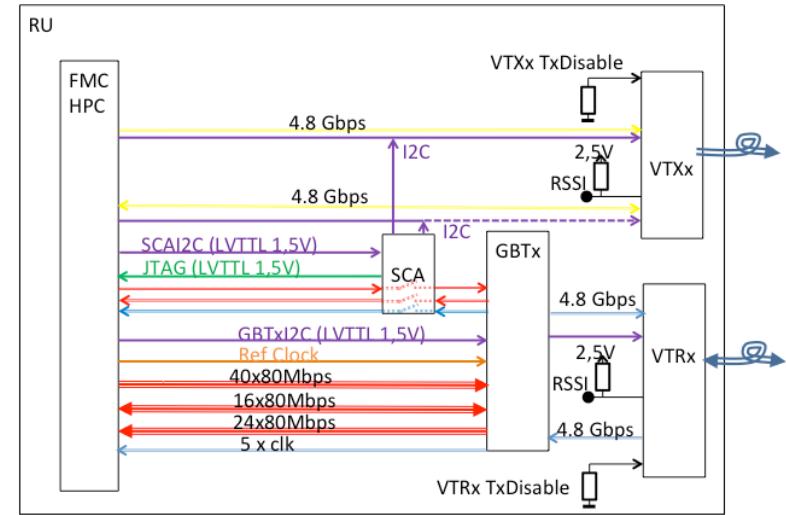
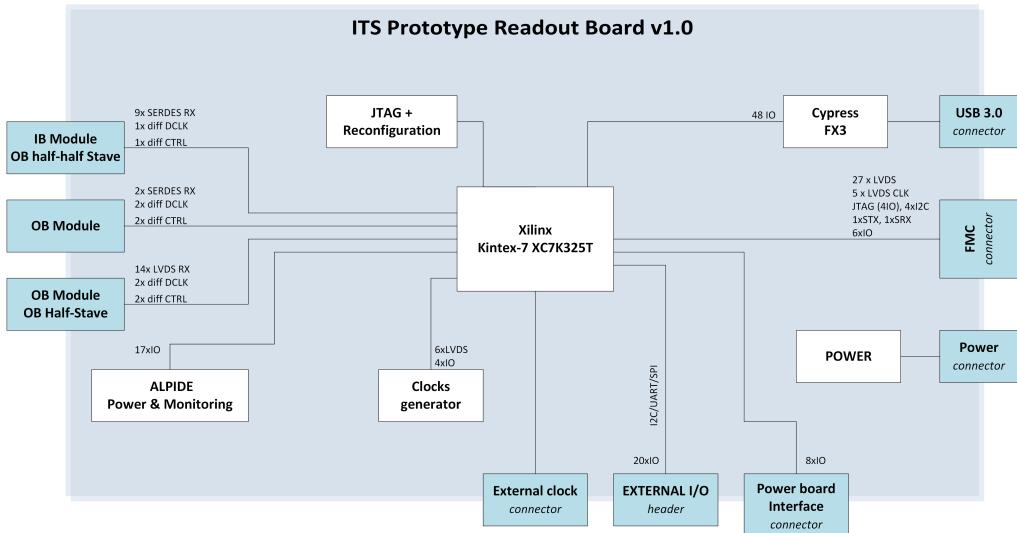
Cables from power supply



Common Readout Unit (Counting Room)

Readout Unit – prototype

First prototype of Readout Unit will be ready in September 2015



Mother Board - schematics completed (CERN)

GBT mezzanine, first round of schematics ready (Nikhef)

- | | |
|---------------------|----------|
| 1. EDR | Aug 2016 |
| 2. PRR | Sep 2017 |
| 3. Start production | Jan 2018 |
| 4. End production | Jul 2018 |